



# Implementation of Advanced Solar-Cell Analysis at Cell Test

Ronald A. Sinton, Adrienne L. Blum

Wes Dobson, Harrison Wilterdink, Justin H. Dinger, Cassidy Sainsbury

Sinton Instruments, Boulder, CO, 80301, USA

# A vision for end-to-end metrology for electronic quality (1999 NREL Silicon Workshop)

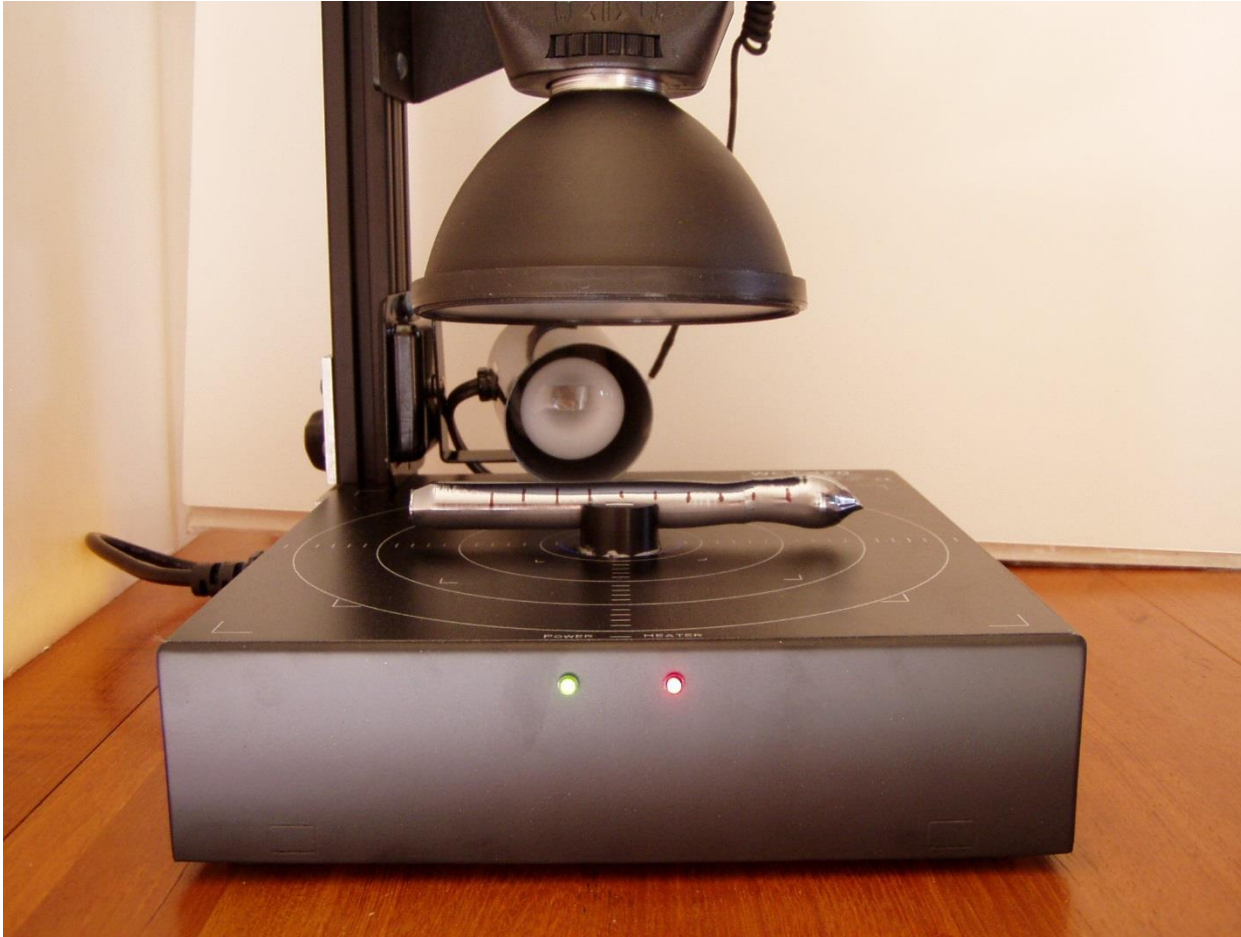
**Table 1.**

Process step	Electronic Process monitors		
	Sheet resistance	Lifetime	Voltage
Incoming wafers	X	X	
Etching		X	
Phosphorus Diffusion	X	X	X
Passivation & AR		X	X
Back metal/anneal	X	X <sup>+</sup>	X
Front Metal/anneal		X <sup>+</sup>	X

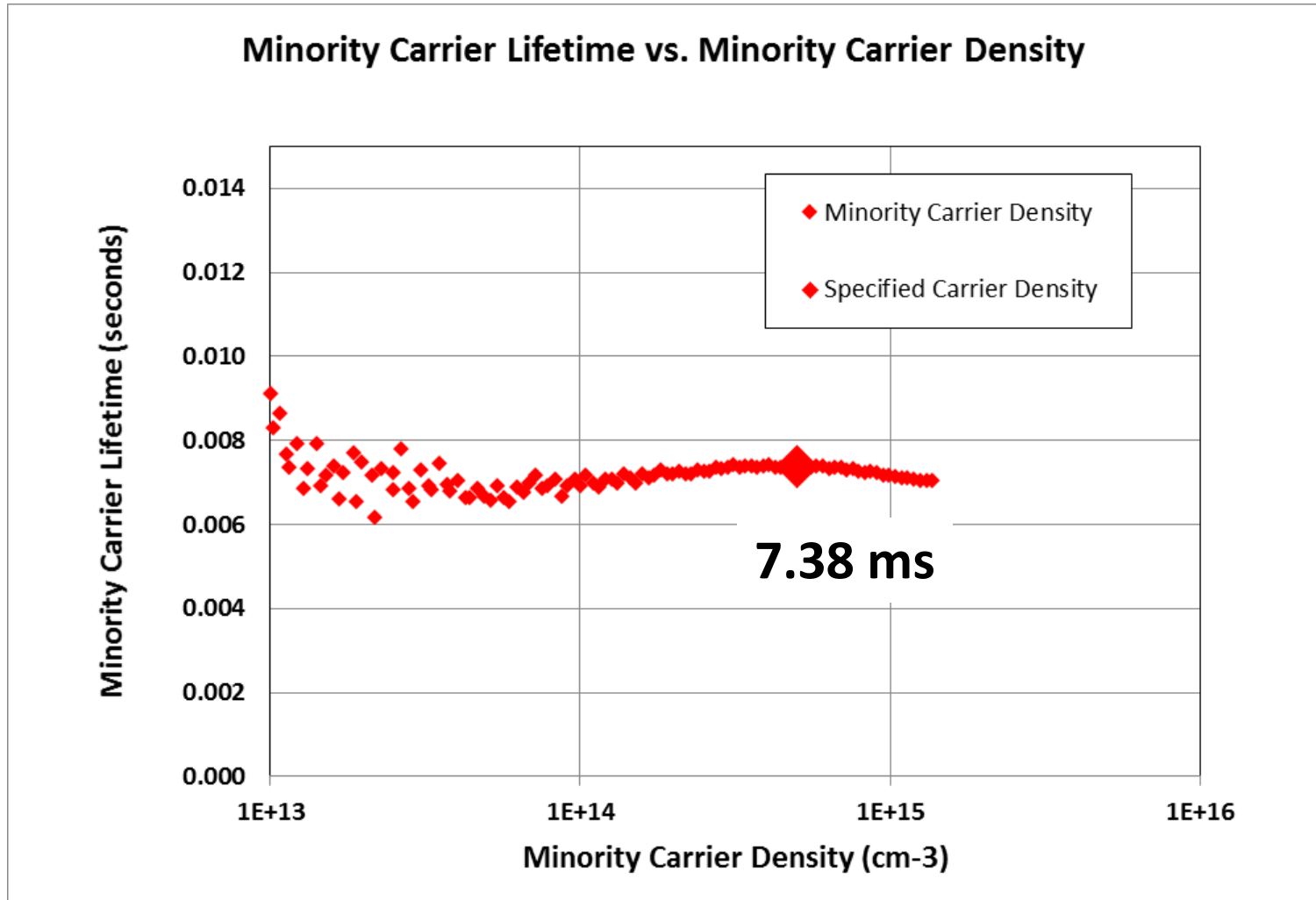
# A vision for end-to-end metrology for electronic quality (2016 NREL Silicon Workshop)

Step	Metric	Fundamental Analysis	Impact Analysis
Feedstock	$\tau$ vs. $\Delta n$	$\tau$ vs. $\Delta n$	Implied IV curve
Crystal	$\tau$ vs. $\Delta n$ , $\Omega$ -cm, trapping	$\tau$ vs. $\Delta n$	Implied IV curve
Wafer	$\tau$ vs. $\Delta n$ , $\Omega$ -cm, trapping	$\tau$ vs. $\Delta n$	Sorting
Dopant diffusion	$\tau$ vs. $\Delta n$ , $\Omega$ -cm, trapping	$\tau$ vs. $\Delta n$	Implied IV curve
Passivation	$\tau$ vs. $\Delta n$ , $\Omega$ -cm, trapping	$\tau$ vs. $\Delta n$	Implied IV curve
Cell	$I$ , $V$ , $R_s$ , $R_{sh}$ , $\tau$ vs. $\Delta n$ , $N_A$	$\tau$ vs. $\Delta n$	Real/pseudo-IV curve
Module	$I$ , $V$ , $R_s$ , $R_{sh}$ , $\tau$ vs. $\Delta n$ , $N_A$	$\tau$ vs. $\Delta n$	Real/pseudo-IV curve
System	$I$ , $V$ , $R_s$ , $R_{sh}$ , $\tau$ vs. $\Delta n$ , $N_A$	$\tau$ vs. $\Delta n$	Real/pseudo-IV curve

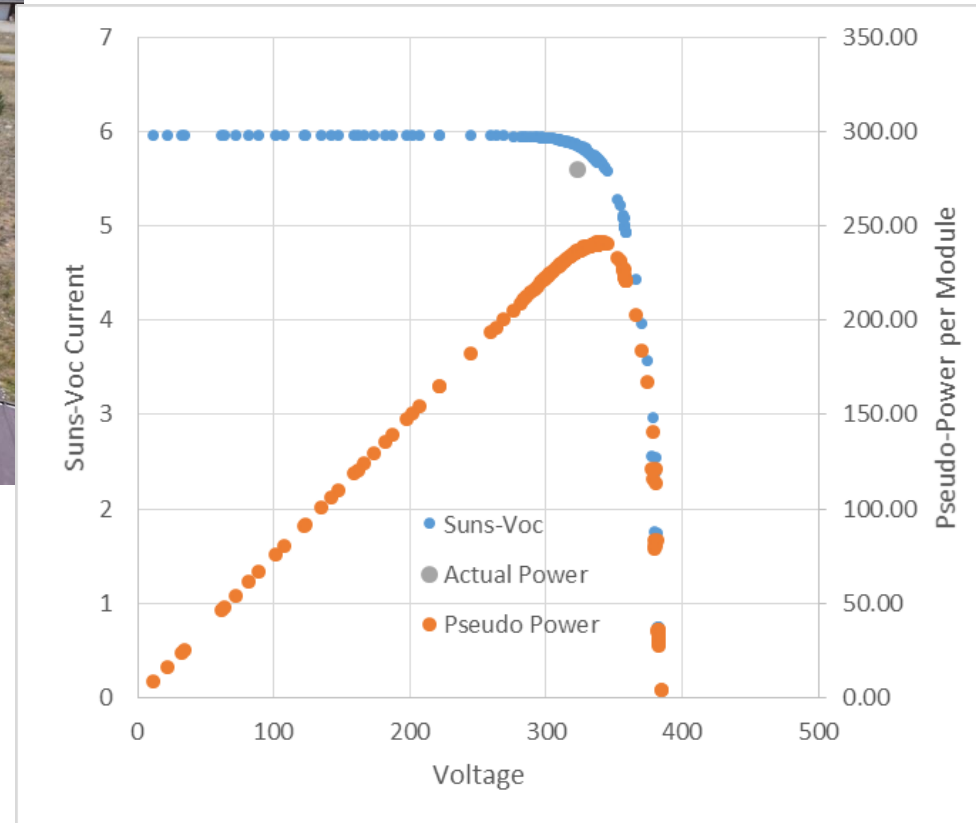
# Feedstock Qualification (Lifetime Test)



# Feedstock Qualification (Lifetime Test)



# Suns- $V_{oc}$ Curves at the Array Level (3.6 KW)



# A vision for end-to-end metrology for electronic quality

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# Cell Test is Unique: 100% Testing of Wafers

**We need to take maximum advantage of this opportunity!**

## **Device physics at cell test:**

- Lifetime vs. injection level
  - bulk lifetime and emitter saturation current densities
- Relevant measurement of series resistance (Suns- $V_{oc}$  curve)
- Time response of high-efficiency cells (Capacitance)
- Examples:
  - n-type high-efficiency solar cell
  - A study of p-type solar cells spanning low to high efficiency
  - Power loss analysis for record-efficiency cell



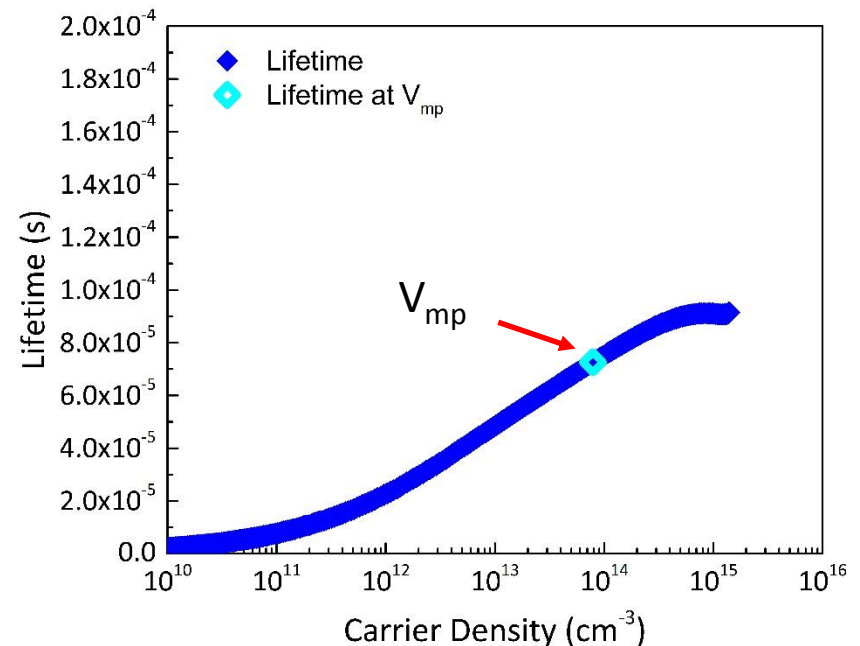
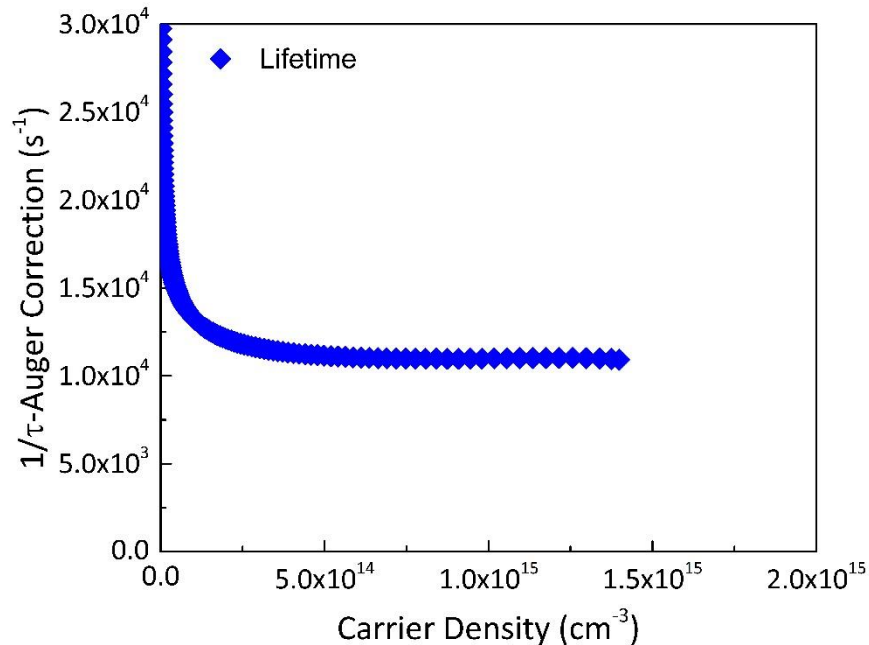
# R&D and Production Cell Testing

- Laboratory cell tester
  - MultiFlash technology
  - Measures full IV curve with conventional parameters ( $\text{Eff}$ ,  $J_{sc}$ ,  $V_{oc}$ ,  $V_{mp}$ ,  $J_{mp}$ ,  $\text{FF}$ )
  - Measures Suns- $V_{oc}$  (pseudo parameters, lifetime vs. injection level,  $J_0$ , BRR, lifetime at  $V_{mp}$ , dark  $R_{sh}$ , SUBSTRATE DOPING)
- Production cell tester
  - Production cell tester (250 MW installed in production to date)
  - All the same parameters
  - New SingleFlash technology enables high-speed testing
  - Potential for 4800 tests per hour
    - $\sim 200\text{ms}$  cell test time of stationary cell

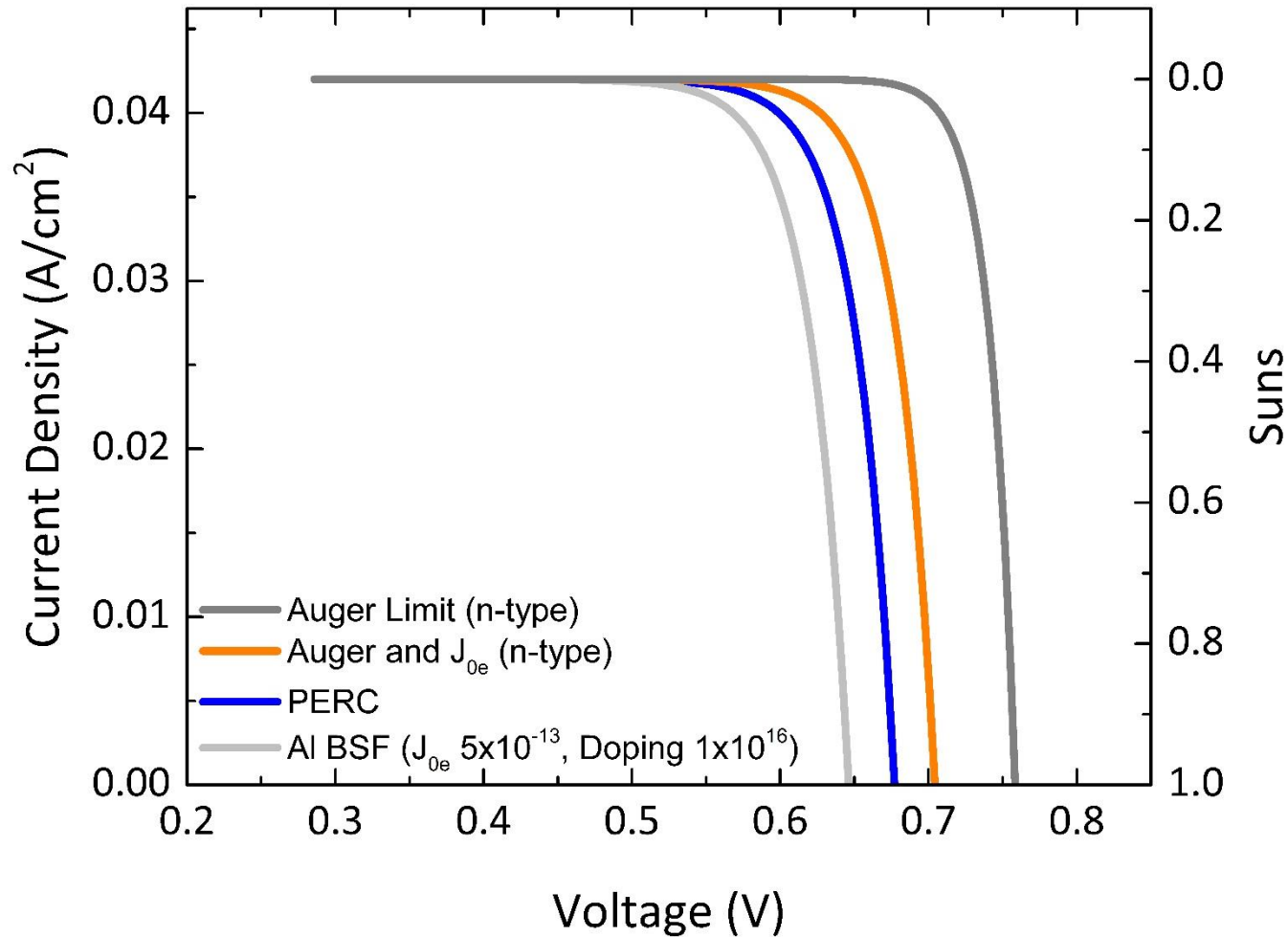
# Methodology: Outline

Parameter	Method
IV parameters	MultiFlash or SingleFlash technology; filtered Xenon light
Substrate doping	Time-dependent continuity equation
Lifetime vs. excess carrier density	Time-dependent Suns- $V_{oc}$ data using doping result
$R_s$	Evaluation of IV and Suns- $V_{oc}$ curves at $J_{mp}$
$R_{sh}$	Ohm-meter in dark at 0 Volts
Voltage (Strategic, 6 points)	8 Channel simultaneous data acquisition
Current	same
Intensity	same (using silicon reference cell)
Temperature	RTD
Capacitance effects	Constant charge method ( EUPVSEC Dresden, 2006)

# Lifetime data: Everyone does this with test wafers and a lifetime tester

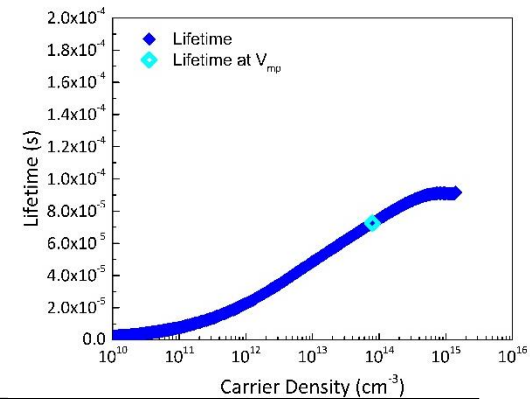


# IV curves: BSF, PERC, n-type, Auger limit



# But it is the same thing! Lifetime data and IV data

$\Delta n_k, \Delta n_{k+1}, \Delta n_{k+2} \dots$



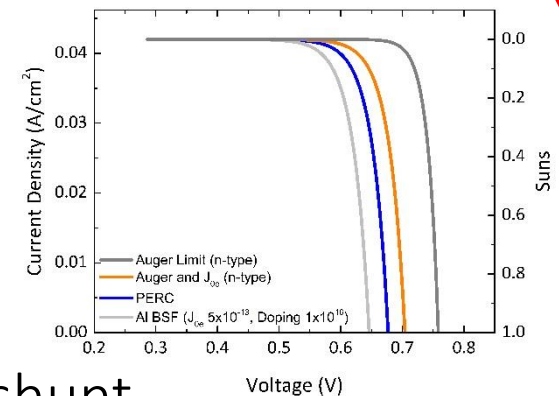
Calculate Recombination:

$$J = \text{Photogeneration} - \text{Recombination} - \frac{V}{R_{sh}}$$

Calculate Voltage:

$$V + JR_s = \frac{kT}{q} \ln \left( \frac{[(N_A + \Delta p)(\Delta n)]}{n_i^2} \right)$$

$(J_k, V_k), (J_{k+1}, V_{k+1}), \dots$



Including series resistance and shunt

# IV in Terms of Emitters and Bulk Lifetime

$$V = \frac{kT}{q} \ln \left[ \frac{(N_A + \Delta p)(\Delta n)}{n_i^2} \right] - JR_s$$

$$\text{Current} = \text{Photogeneration} - \left[ \frac{\Delta n q W}{\tau_{bulk}} + [J_{0front} + J_{0back}] \frac{(N_A + \Delta p)(\Delta n)}{n_i^2} \right] - \frac{V}{R_{sh}}$$

[Recombination]

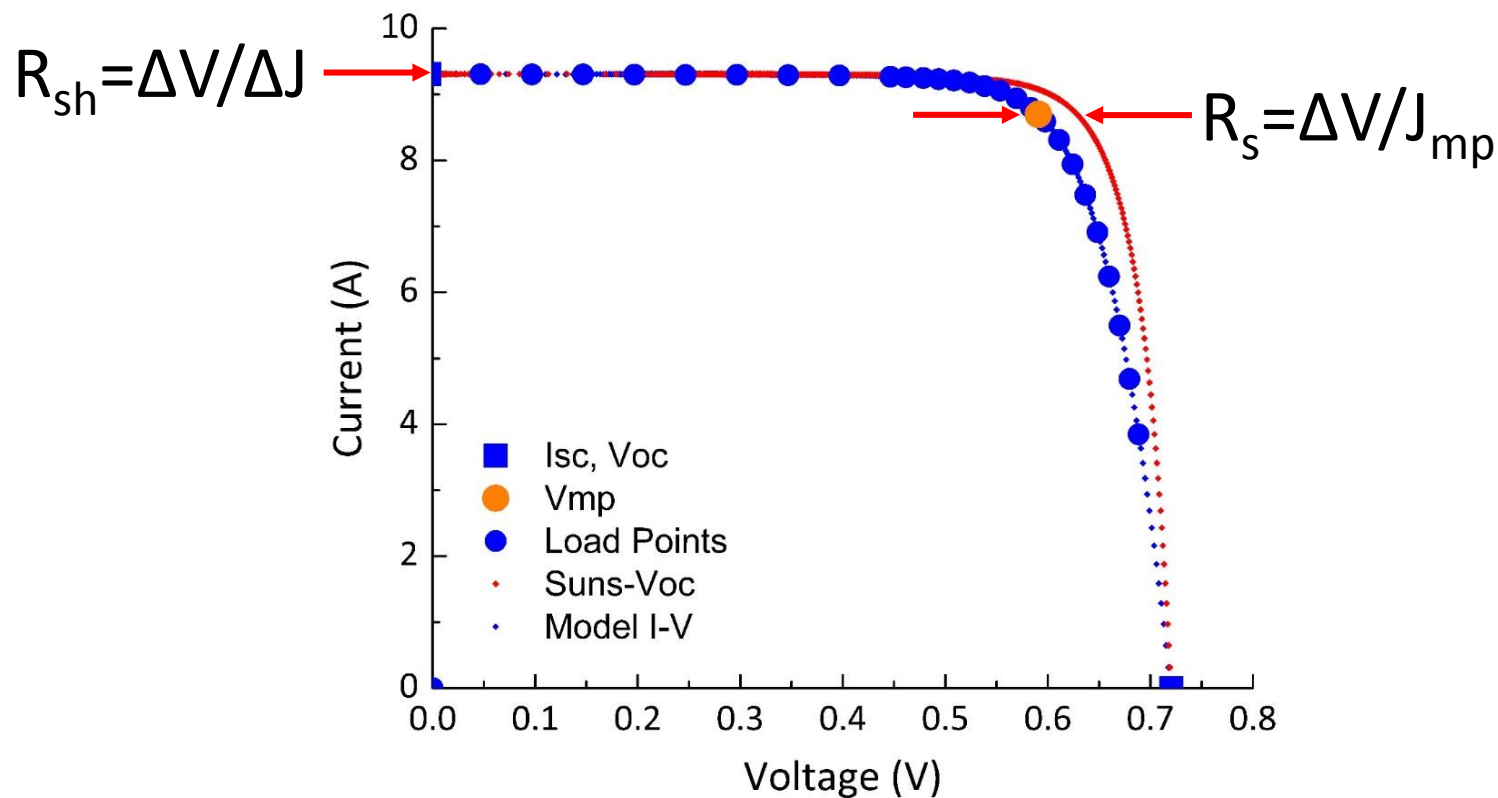
“Thin-base limit”

# IV in Terms of Emitters and Bulk Lifetime

$$V = \frac{kT}{q} \ln \left[ \frac{(N_A + \Delta p)(\Delta n)}{n_i^2} \right] - JR_s$$

$$\text{Current} = \text{Photogeneration} - \left[ \frac{\Delta n q W}{\tau_{bulk}} + [J_{0front} + J_{0back}] \frac{(N_A + \Delta p)(\Delta n)}{n_i^2} \right] - \frac{V}{R_{sh}}$$

# $R_s$ Measurement Using Suns- $V_{oc}$ Curve



$R_s$  from Suns- $V_{oc}$  does NOT depend on quality of fit to a model  
(no 1- or 2-diode equations or such nonsense)



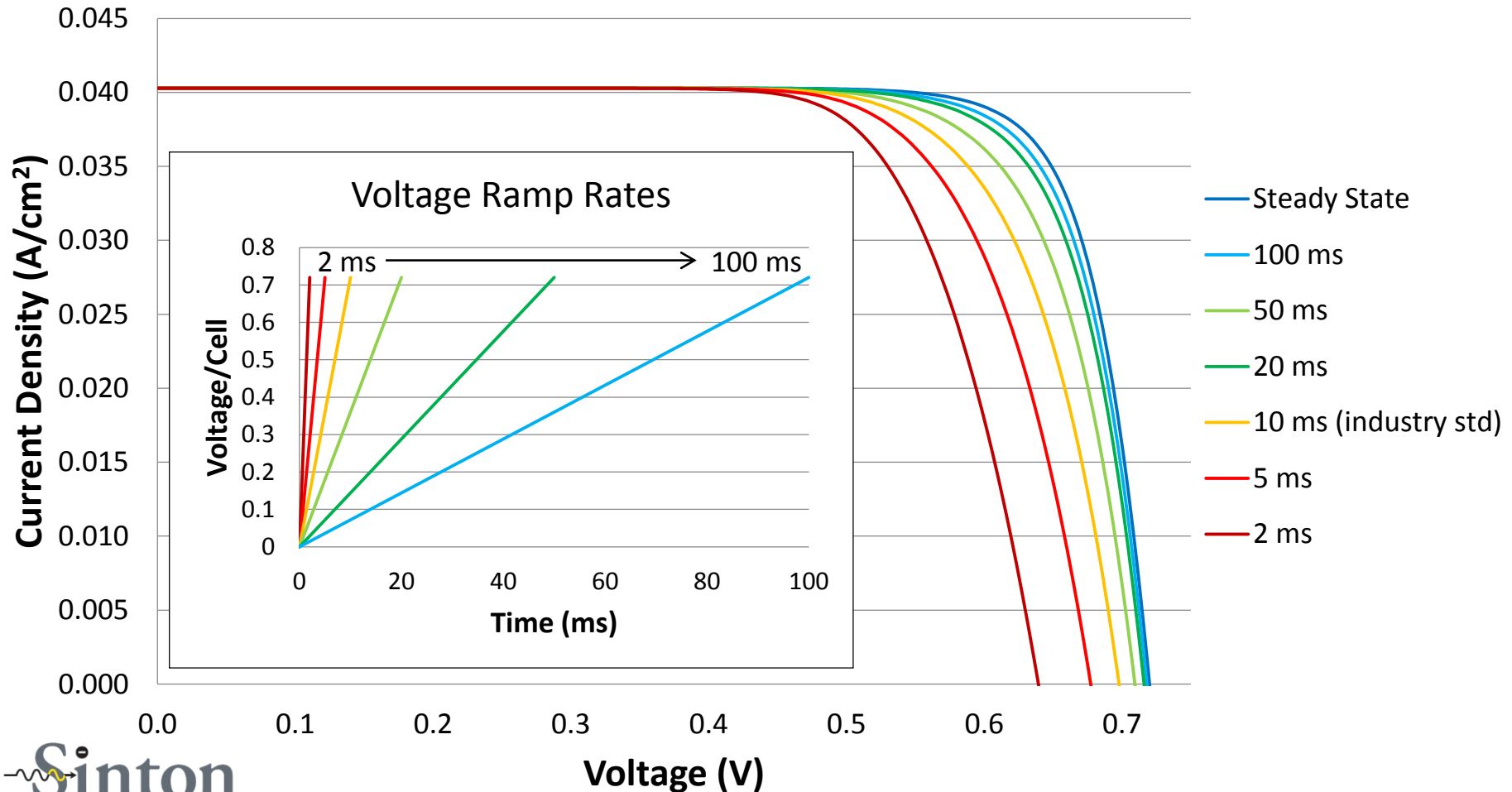
# Biggest Challenge with High-Efficiency n-type

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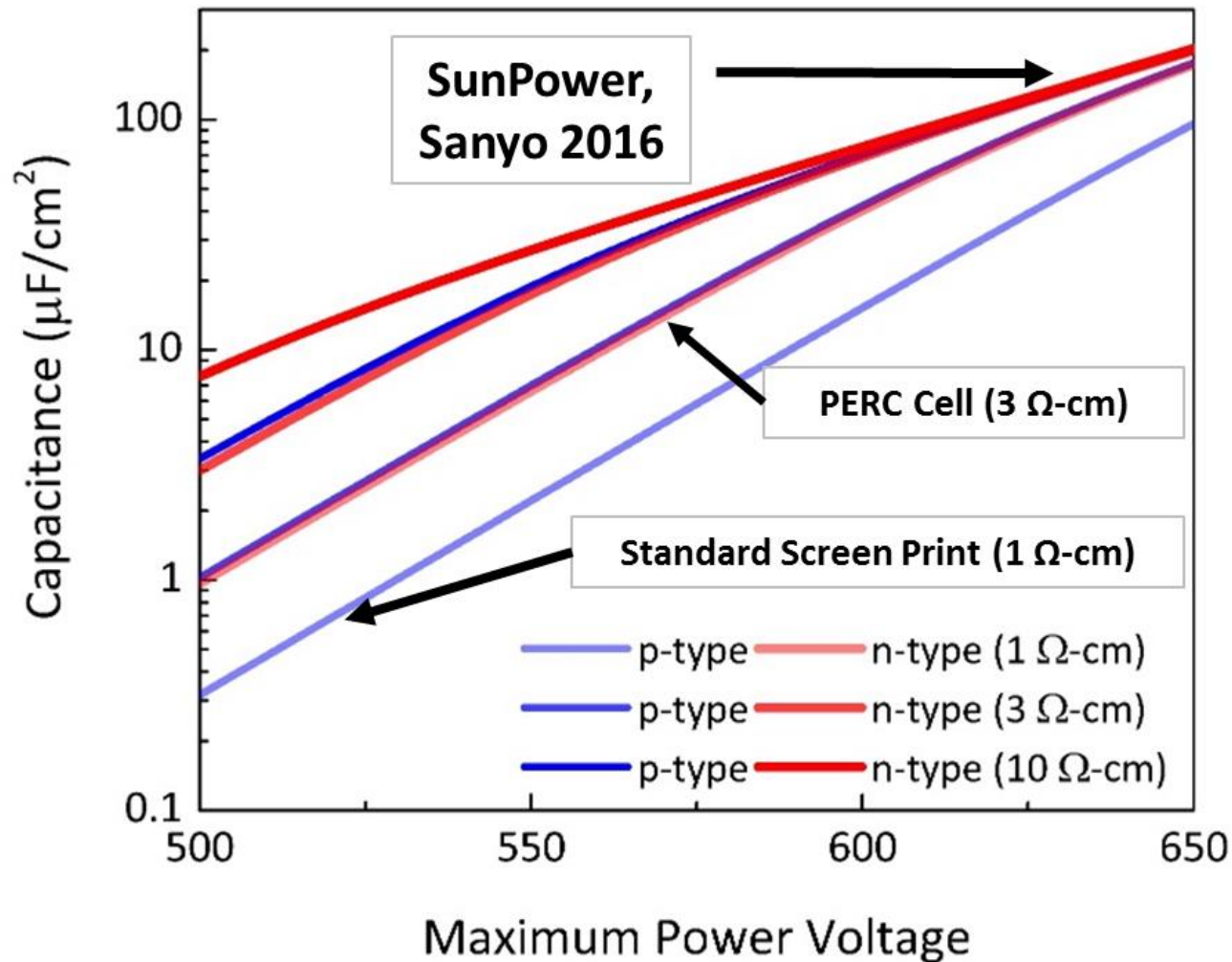
Time response of high-efficiency cells (capacitance)

# Ramp-rate Artifacts (PC1D simulations)

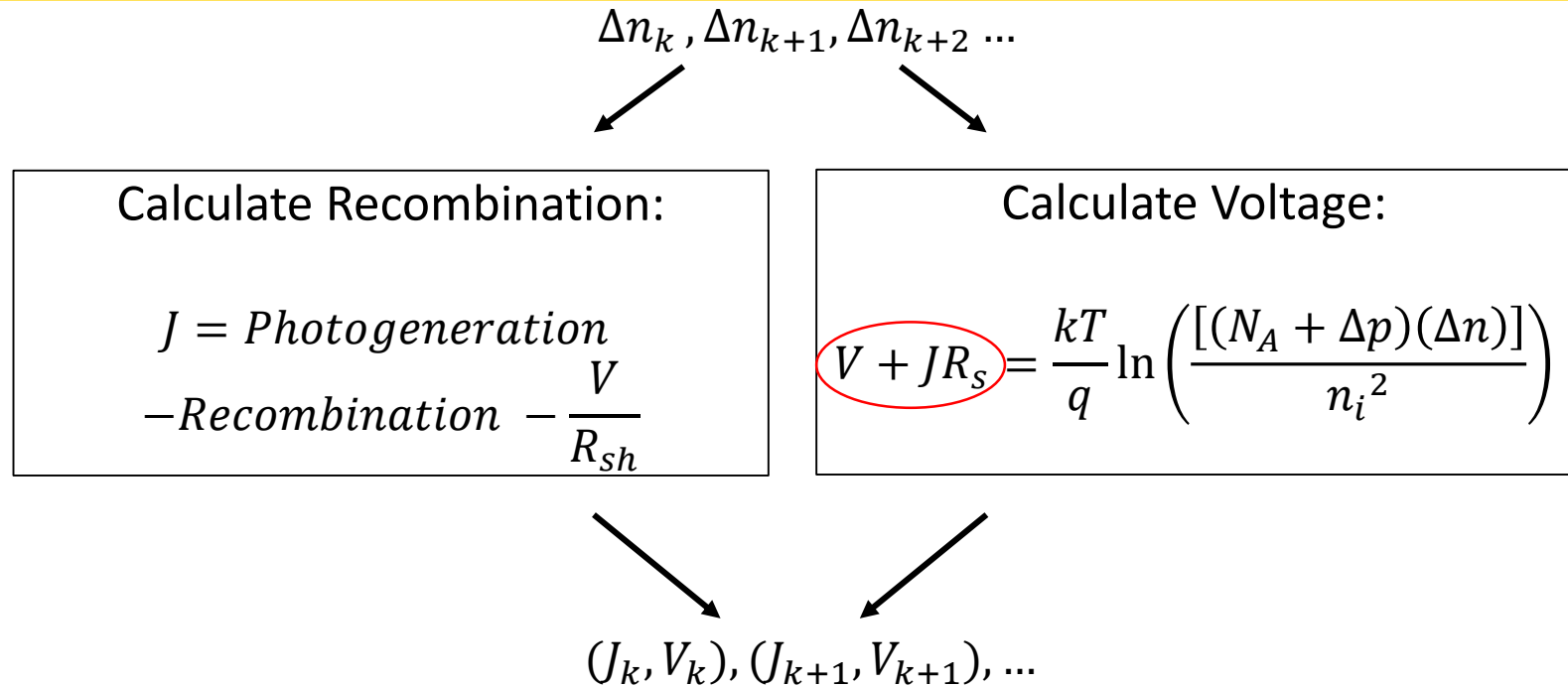
Modeled Si cell ( $V_{oc} = 720$  mV, thickness =  $200\text{ }\mu\text{m}$ )  
IV curves at different ramp rates



# High-Efficiency n-type Cells: 200X Higher Capacitance!



# Eliminating errors due to slow time response during flash testing



**Solution: Test under constant charge conditions:**

Measure  $V$  and  $J$ , while holding  $(V + J \times R_s)$  constant using a feedback circuit. 10 years of industrial production and R&D experience with this technique.

# Eliminating errors due to slow time response during flash testing

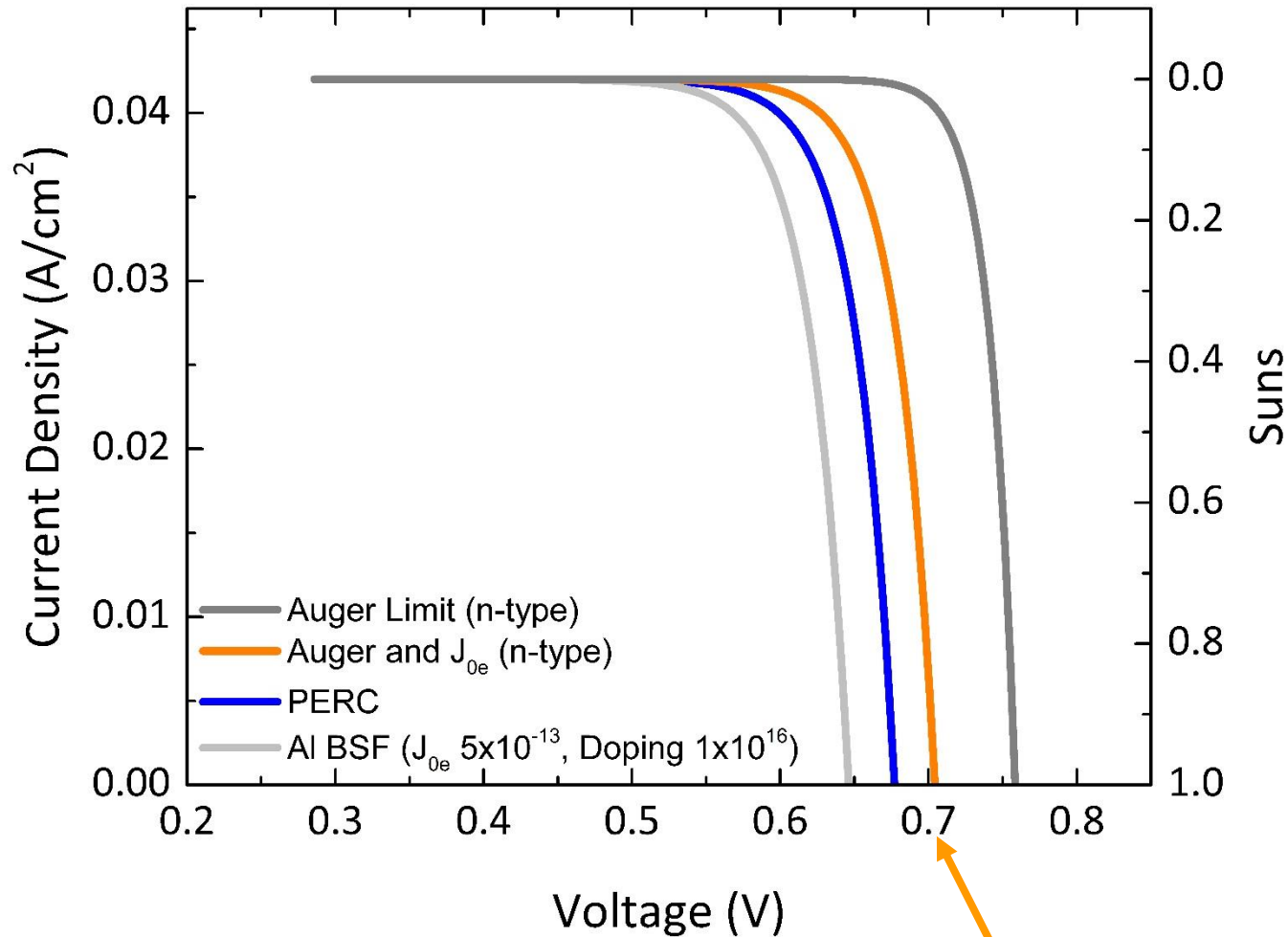
- [SintonDresden2006.pdf](#)



**Solution: Test under constant charge conditions:**

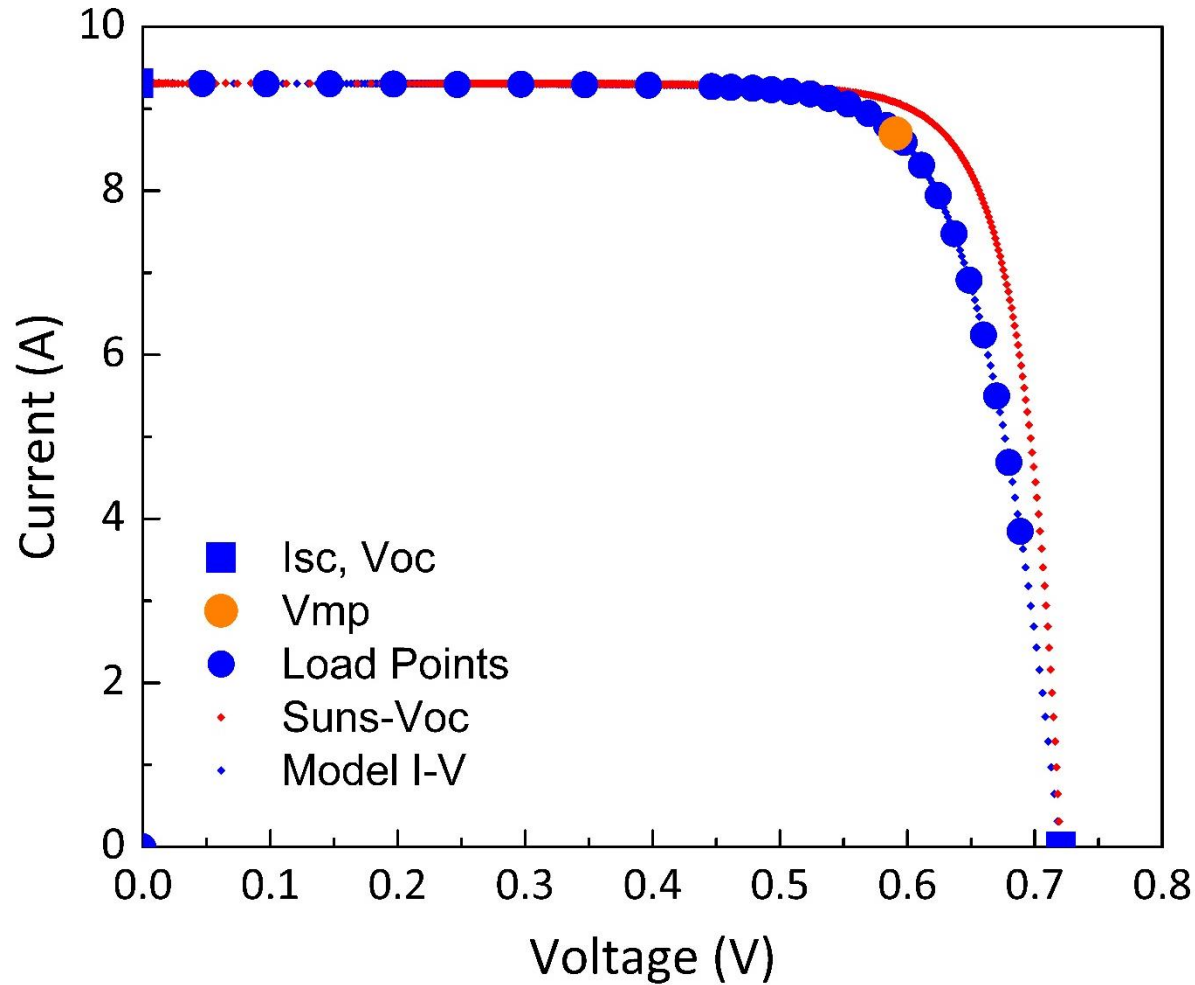
Measure  $V$  and  $J$ , while holding  $(V + J \times R_s)$  constant using a feedback circuit. 10 years of industrial production and R&D experience with this technique.

# Example: IV test of a high-efficiency n-type cell

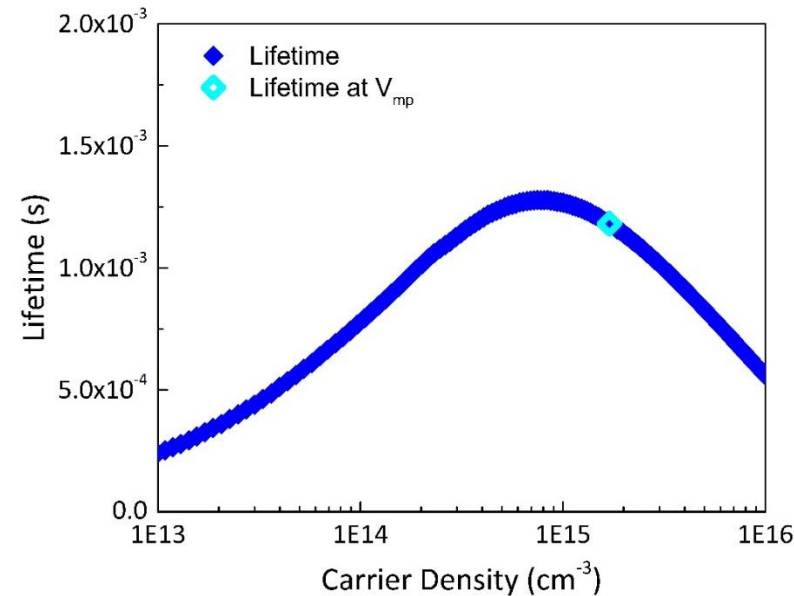
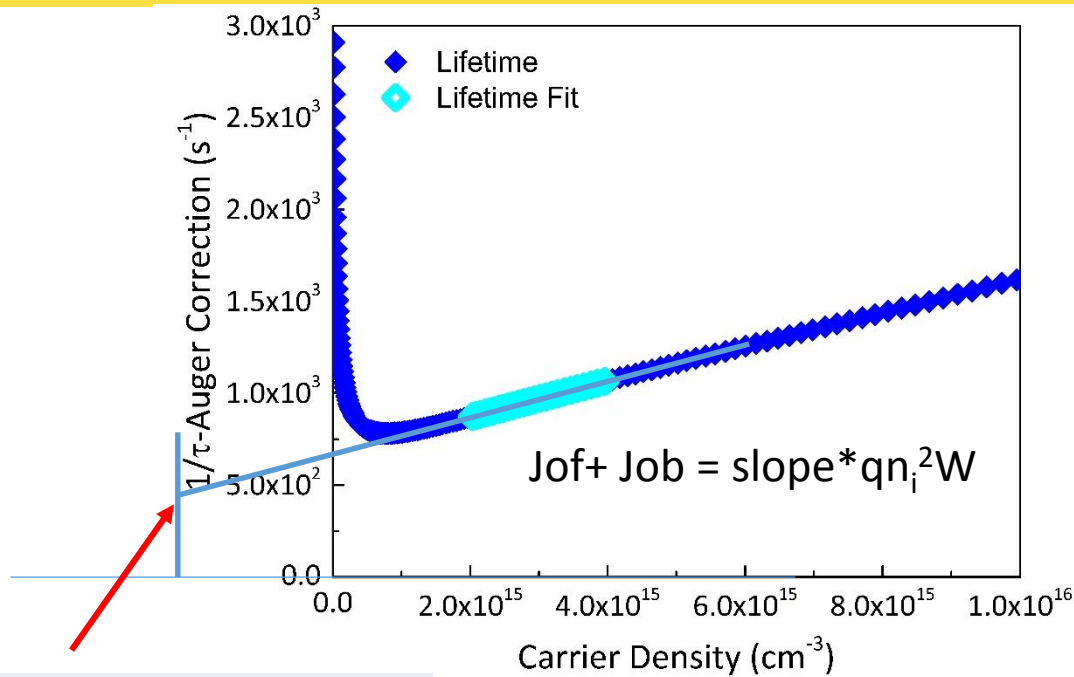


High-Efficiency n-type

# IV-test example: N-type high efficiency



# IV-test example: N-type high efficiency



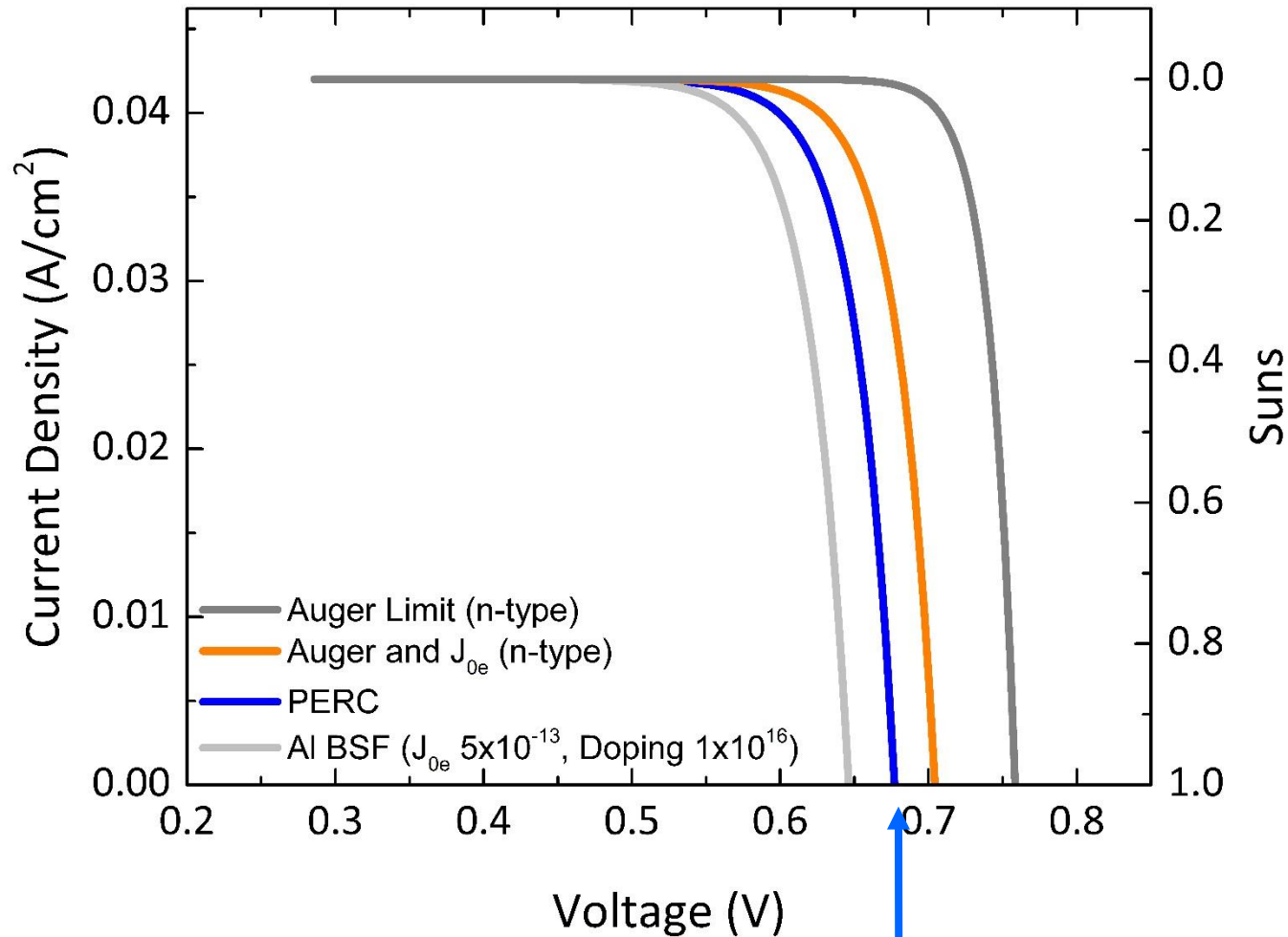


# IV-test Example: n-type High Efficiency

Normalized Results	
Parameter	Result
$J_{sc}$ (A/cm <sup>2</sup> )	0.03786
$V_{oc}$ (V/cell)	0.7201
$J_{mp}$ (A/cm <sup>2</sup> )	0.03535
$V_{mp}$ (V/cell)	0.5912
$P_{mp}$ (W/cm <sup>2</sup> )	0.209
$R_{sh}$ (Ω-cm <sup>2</sup> )	140151
$R_s$ (Ω-cm <sup>2</sup> )	1.058
Cell Efficiency (%)	20.9

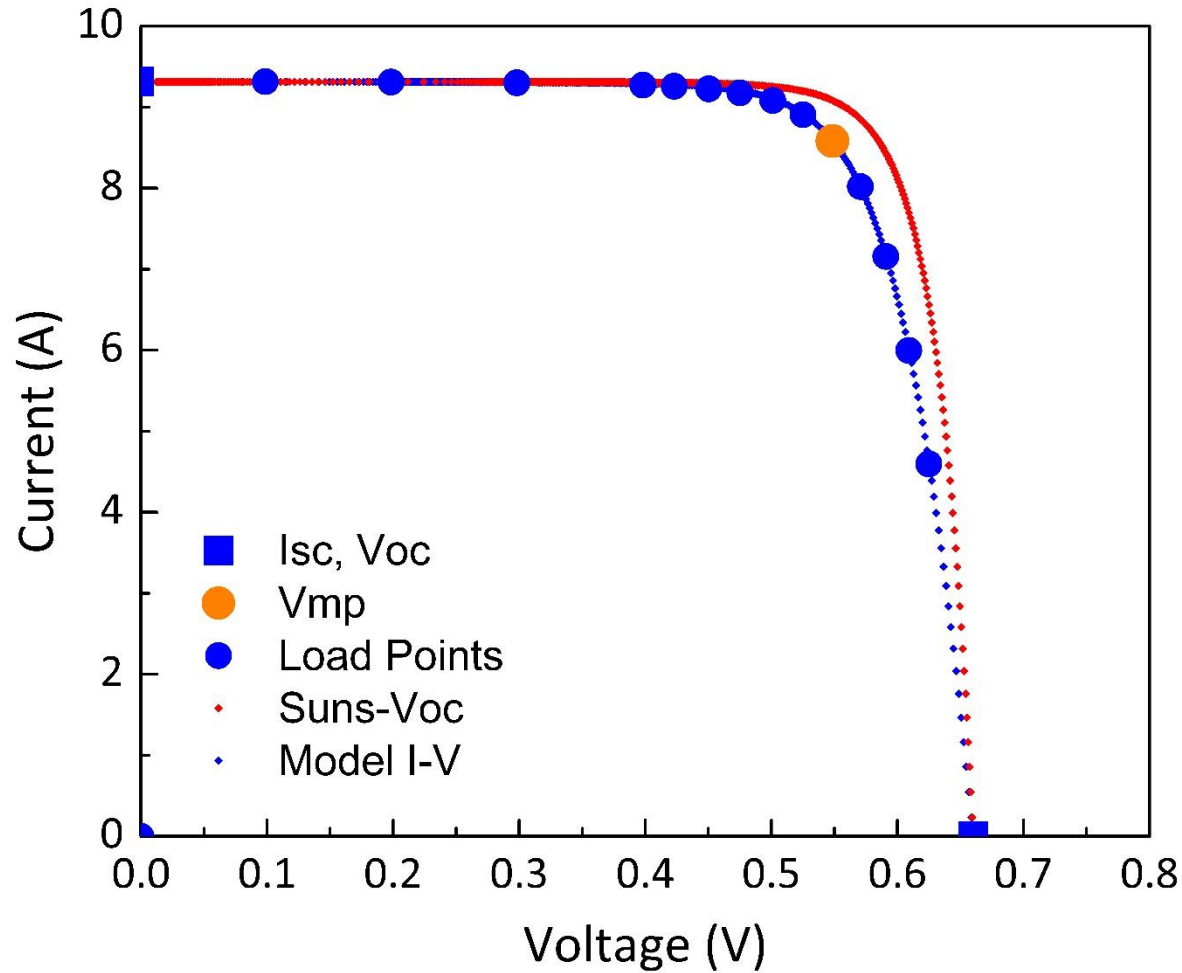
Suns-Voc Outputs	
Parameter	Result
$pJ_{mp}$ (A/cm <sup>2</sup> )	0.03786
$pV_{mp}$ (V/cell)	0.7201
$pP_{mp}$ (W/cm <sup>2</sup> )	0.209
$pFF$ (%)	81.6
$pEfficiency$ (%)	22.25
$n$ @ 1 sun	1.141
$n$ @ 0.1 suns	1.413
$J_{01}$ (A/cm <sup>2</sup> )	$2.478 \times 10^{-14}$
$J_{02}$ (A/cm <sup>2</sup> )	$7.956 \times 10^{-9}$
$J_{0e}$ (fA/cm <sup>2</sup> )	15.08
Est. Bulk Lifetime (μs)	1632
BRR (Hz)	612.9
Lifetime @ $V_{mp}$ (μs)	1186
Doping (cm <sup>-3</sup> )	$7.27 \times 10^{14}$
Measured Resistivity (Ω-cm)	6.307
Lifetime Fit $R^2$	1

# Example: IV test of a PERC cell

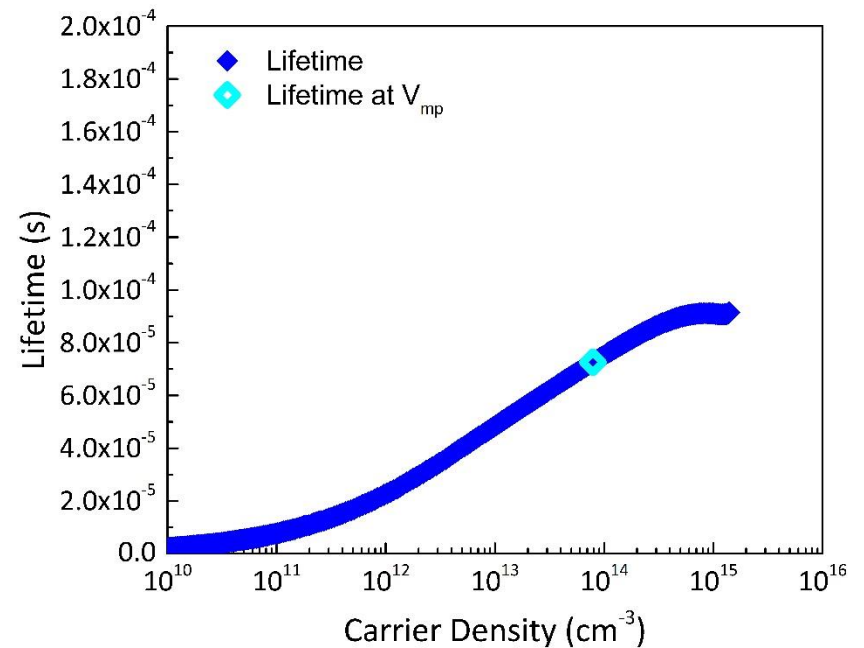
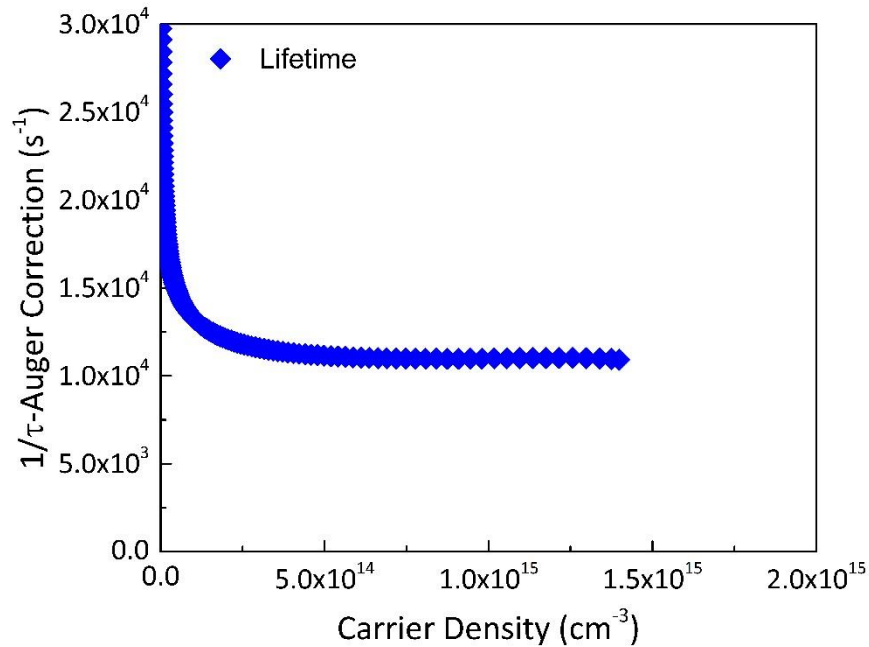


PERC cell

# Example: IV test of a PERC cell



# IV-test example: PERC cells





# Lifetime and Substrate Doping Measurements of Solar Cells and Application to In-Line Process Control

Adrienne L. Blum

Wes Dobson, Harrison Wilterdink, Justin H. Dinger,

Ronald A. Sinton

*Sinton Instruments, Boulder, CO, 80301, USA*

IEEE PVSC, Portland, Oregon, 2016

# Measurement Samples: P-type Study

- P-type cells processed with varying techniques:
  - Multi-crystalline Al BSF cells
  - High Performance Multi-crystalline Al BSF cells
  - Multi crystalline PERC cells
  - Monocrystalline PERC cells
  - Monocrystalline PERC cells

# Doping Measurement: An Opportunity

- Substrate doping and  $\tau$  vs.  $\Delta n$  at the cell level
  - Substrate doping
    - Wafer position in ingot or brick  $\rightarrow$  prediction of [O]/other impurities  $\rightarrow$  potential prediction of LID behavior
    - Information relevant to lateral series resistance in PERC cells
    - Gives final substrate doping, including changes from high temp steps
  - Effective lifetime
    - Surface passivation quality
    - Substrate quality
    - Contamination during high-temperature processing

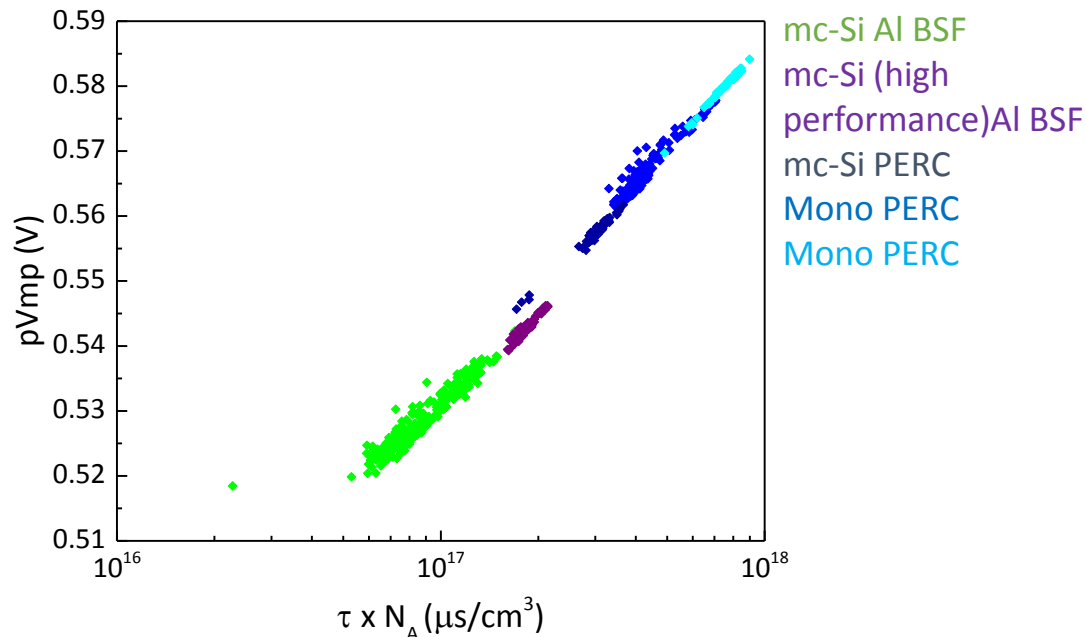
# Measurement Parameters

- Analyze  $pV_{mp}$  and efficiency dependence on substrate doping ( $N_A$ ) and effective lifetime ( $\tau_{eff}$ )
  - $pV_{mp}$  is used because the five groups of cells come from different processing techniques, allows for a comparison independent of  $R_s$
- $pV_{mp}$ : 515-584mV
- Efficiency: 15.8-21%
- $\tau_{eff}$ : 5-100 $\mu$ s
- $N_A$ :  $5 \times 10^{15}$ - $3 \times 10^{16} \text{cm}^{-3}$



# $pV_{mp}$ and Efficiency Correlate to $\tau \times N_A$

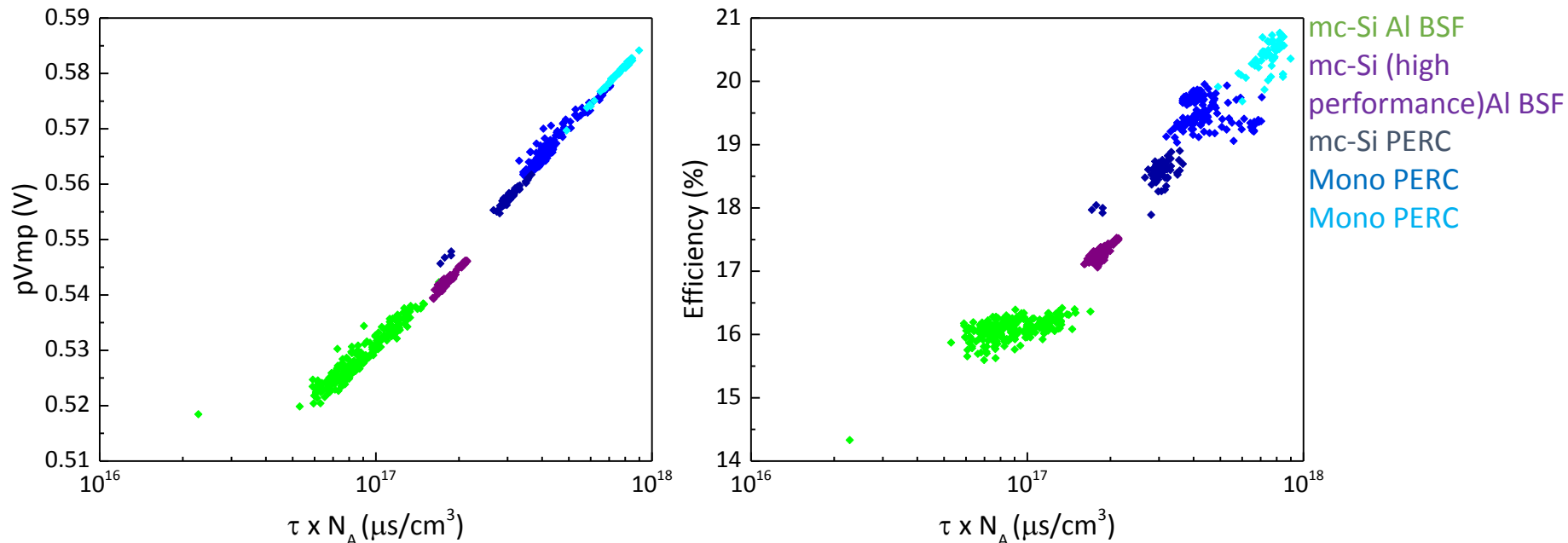
- Five different cell processing techniques all follow the same trend



$$V + R_s J = \frac{kT}{q} \ln \left[ \frac{(J_{sc} - J) (N_A + \Delta n) \tau_{eff}}{q W n_i^2} \right]$$

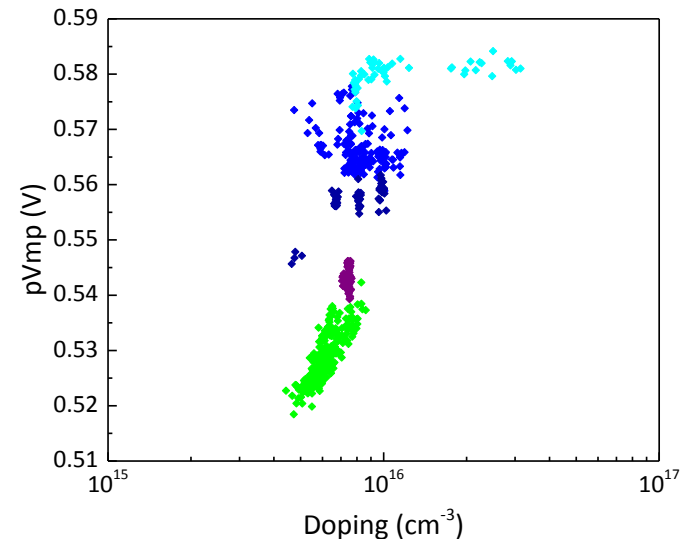
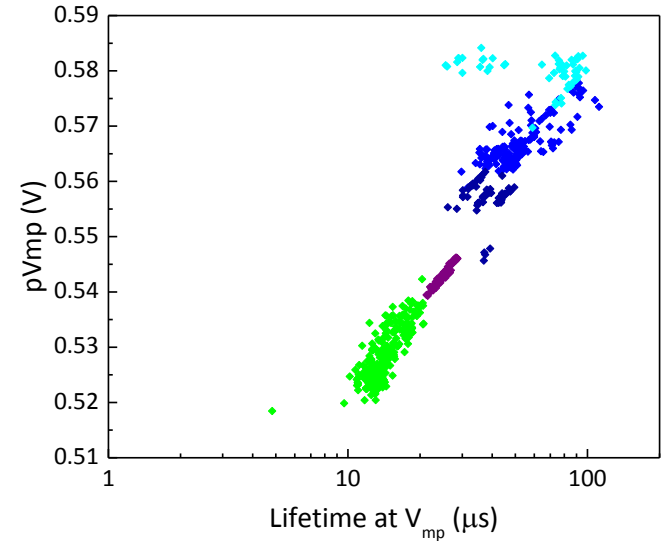
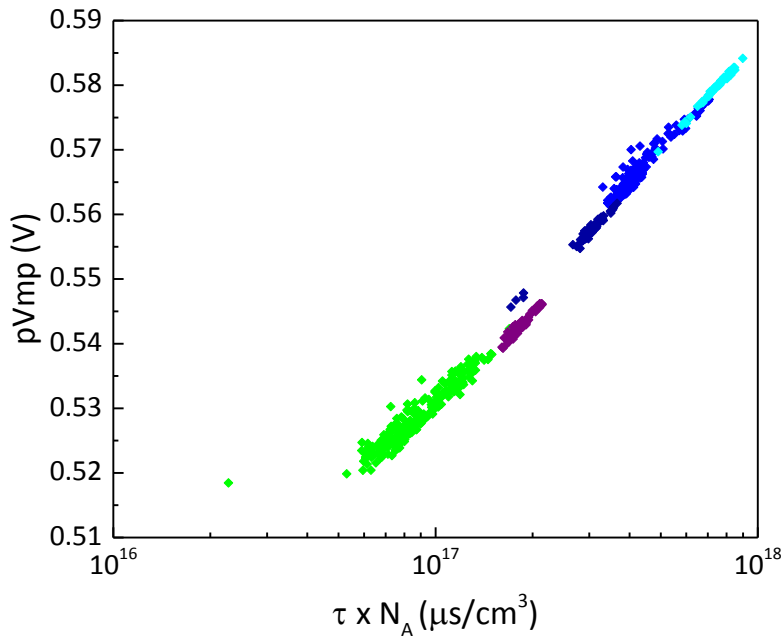
# $pV_{mp}$ and Efficiency Correlate to $\tau \times N_A$

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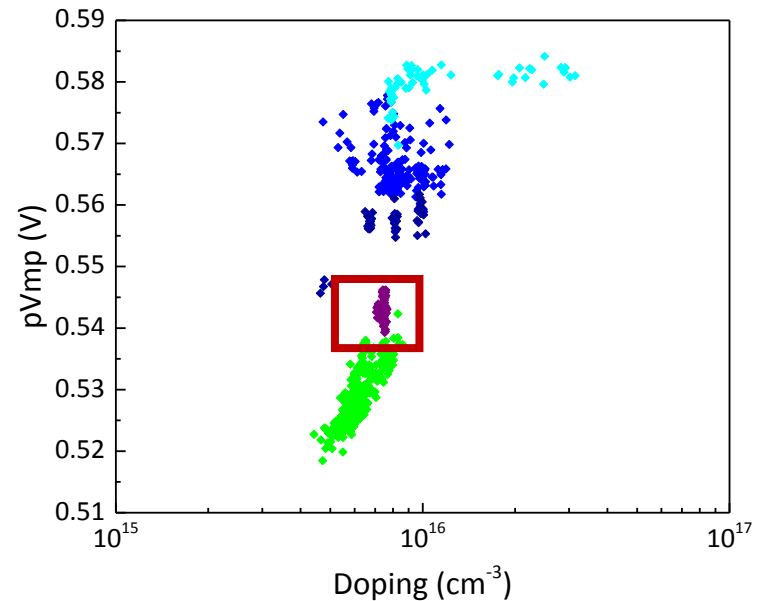
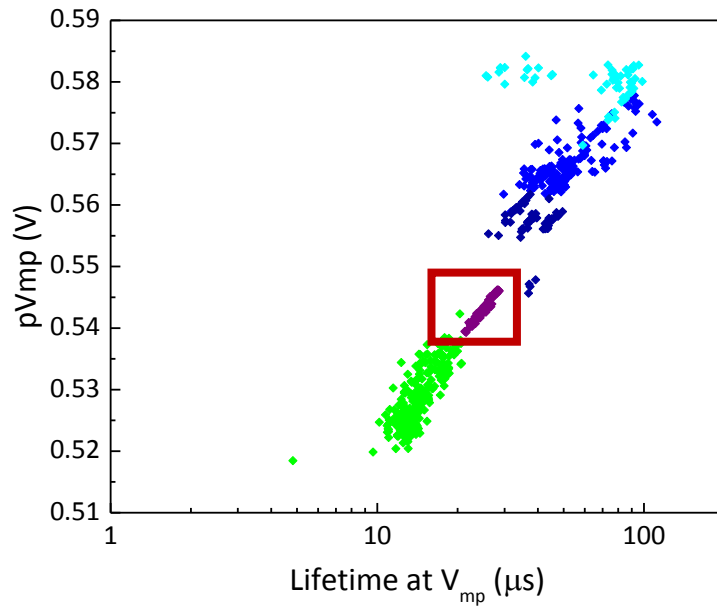
$$V + R_s J = \frac{kT}{q} \ln \left[ \frac{(J_{sc} - J) (N_A + \Delta n) \tau_{eff}}{q W n_i^2} \right]$$

# Substrate Doping Doesn't Tell the Whole Story



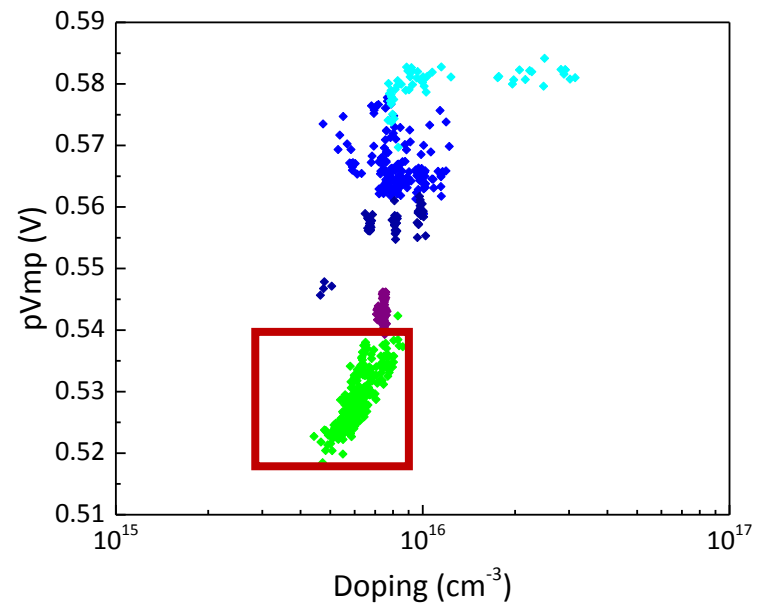
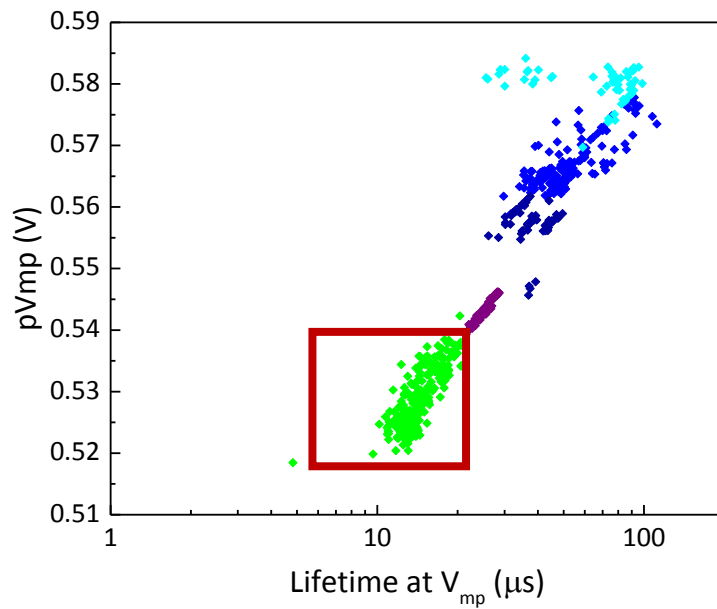
# High Performance Multi Al BSF

- $pV_{mp}$  ranging from 518.5 to 542.3 mV
- Similar substrate doping  $\sim 7.5 \times 10^{15} \text{ cm}^{-3}$ 
  - No  $pV_{mp}$  trend due to doping
- Clear trend due to lifetime



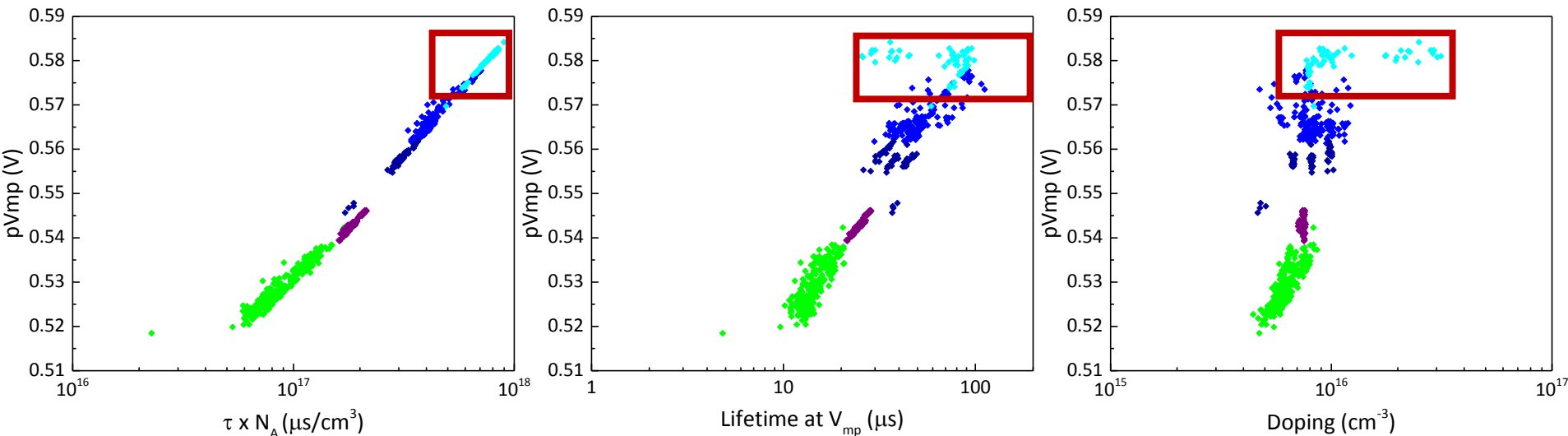
# Multi-crystalline Al BSF

- $pV_{mp}$  correlation to both doping and lifetime
- Indicating independent effects of these parameters
  - Expected for variations in wafers from multi-crystalline bricks



# Mono-crystalline PERC

- Strong dependence on lifetime-doping product
- No distinct correlation to lifetime or doping independently
- Cause of high quality substrate
  - Bulk lifetime is very good
  - Lifetime-doping product is determined by the front and back  $J_{0e}$



$$(N_A + \Delta n)\tau_{eff} = \frac{1}{\frac{1}{\tau_{bulk}(N_A + \Delta n)} + \frac{J_{o front} + J_{o back}}{qn_i^2 W}}$$

# Big Data: Simple Example

- Measure 200,000 multi-crystalline cells (2 days of data)
  - Resistivity varies from 1-3  $\Omega$ -cm
- If you want to isolate the dependence on doping, then:
  - Compare a histogram of cells with 10,000 1  $\Omega$ -cm resistivity with a histogram of 10,000, 2  $\Omega$ -cm cells
  - The resulting distributions (for each) are independent of the effects of doping, effectively isolating the experiment to look at other variables
  - Differences between the histograms indicate doping dependence

# Last Example: Energy-loss analysis at IV-test

Based on results published by SunPower at PVSC

David D. Smith et al. “Silicon Solar Cells with Total Area Efficiency over 25%” IEEE PVSC June 2016.



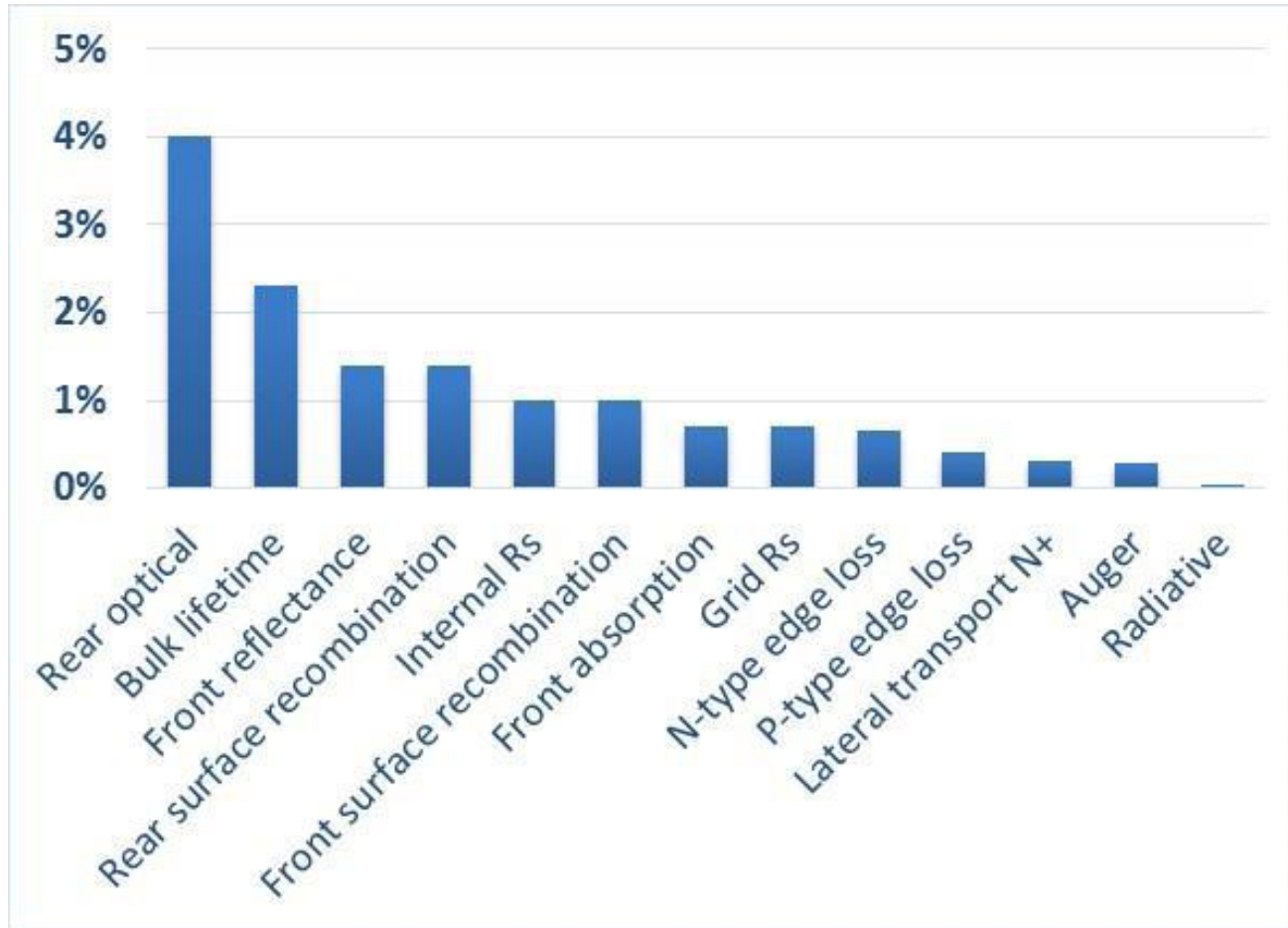
# Example of use of lifetime data at cell test: 25.2% n-type cell (SunPower)

TABLE I  
SUMMARY OF ELECTRICAL DATA

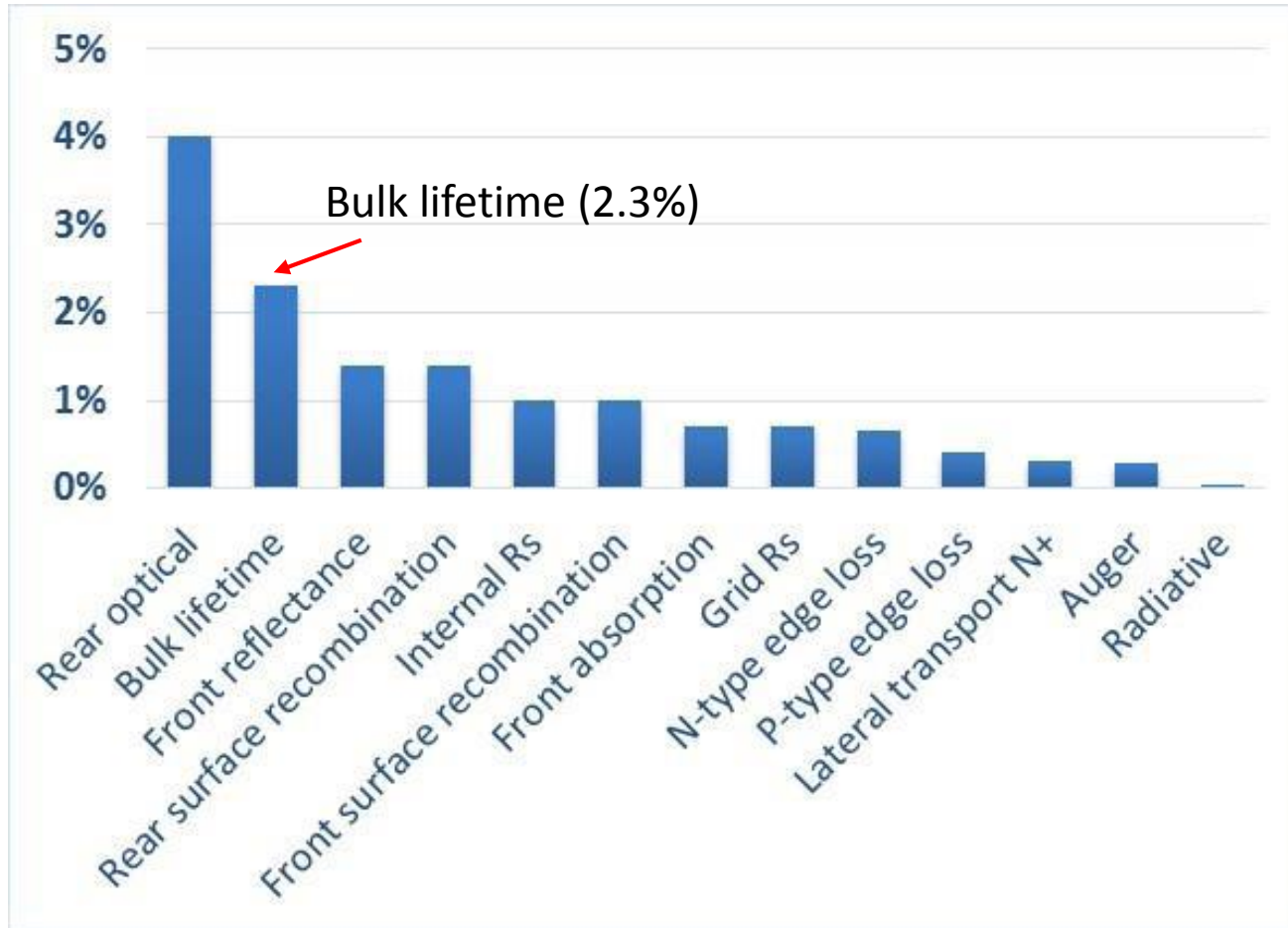
Area (cm <sup>2</sup> )	Voc (mV)	Jsc (mA/cm <sup>2</sup> )	FF (%)	Vmp (mV)	Eff (%)
153.49	737	41.33	82.7	643.8	25.2 %

Cells used to demonstrate 24.1% module efficiency

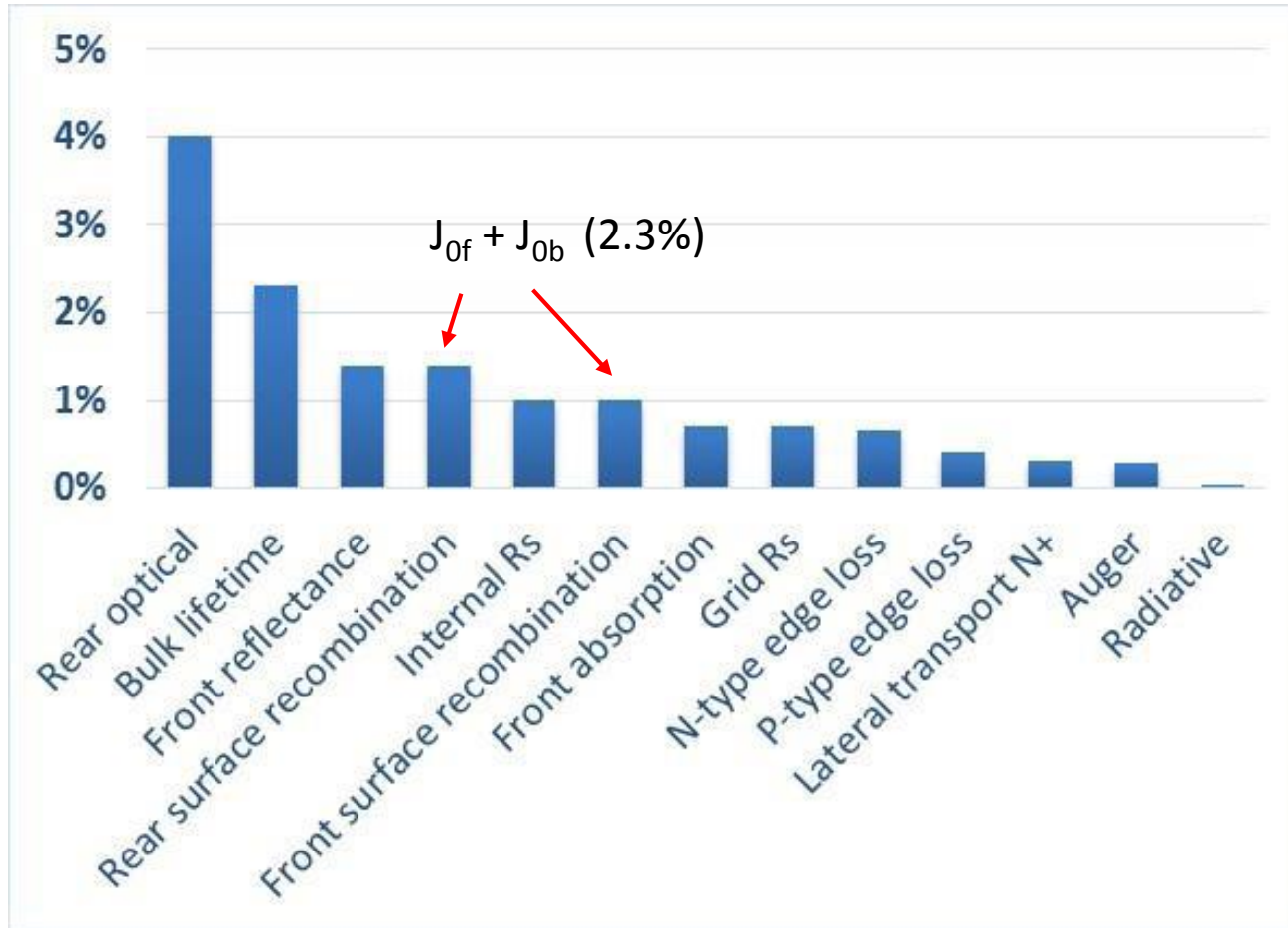
# Loss analysis presented by SunPower at PVSC



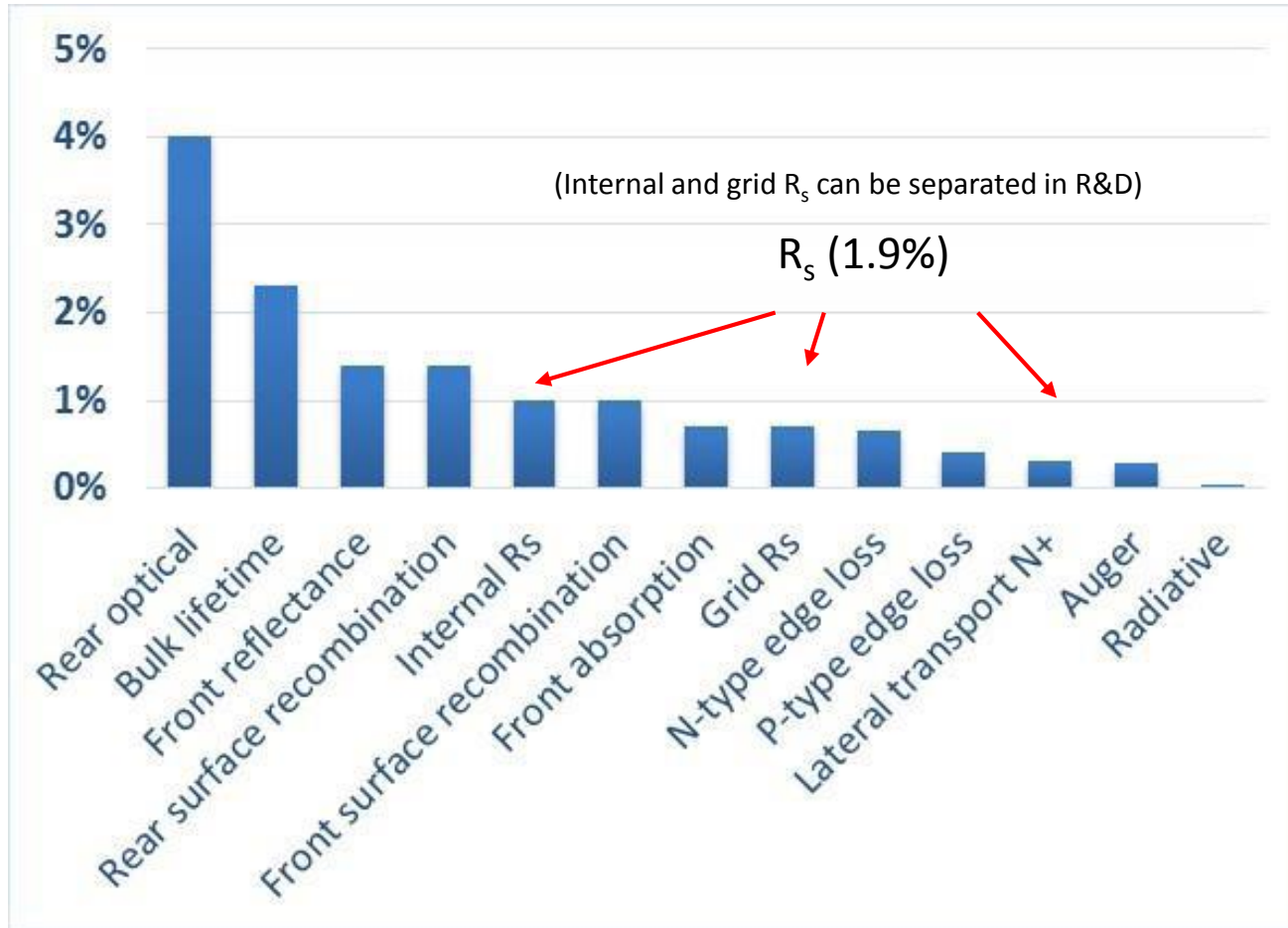
# Loss analysis: Bulk Lifetime



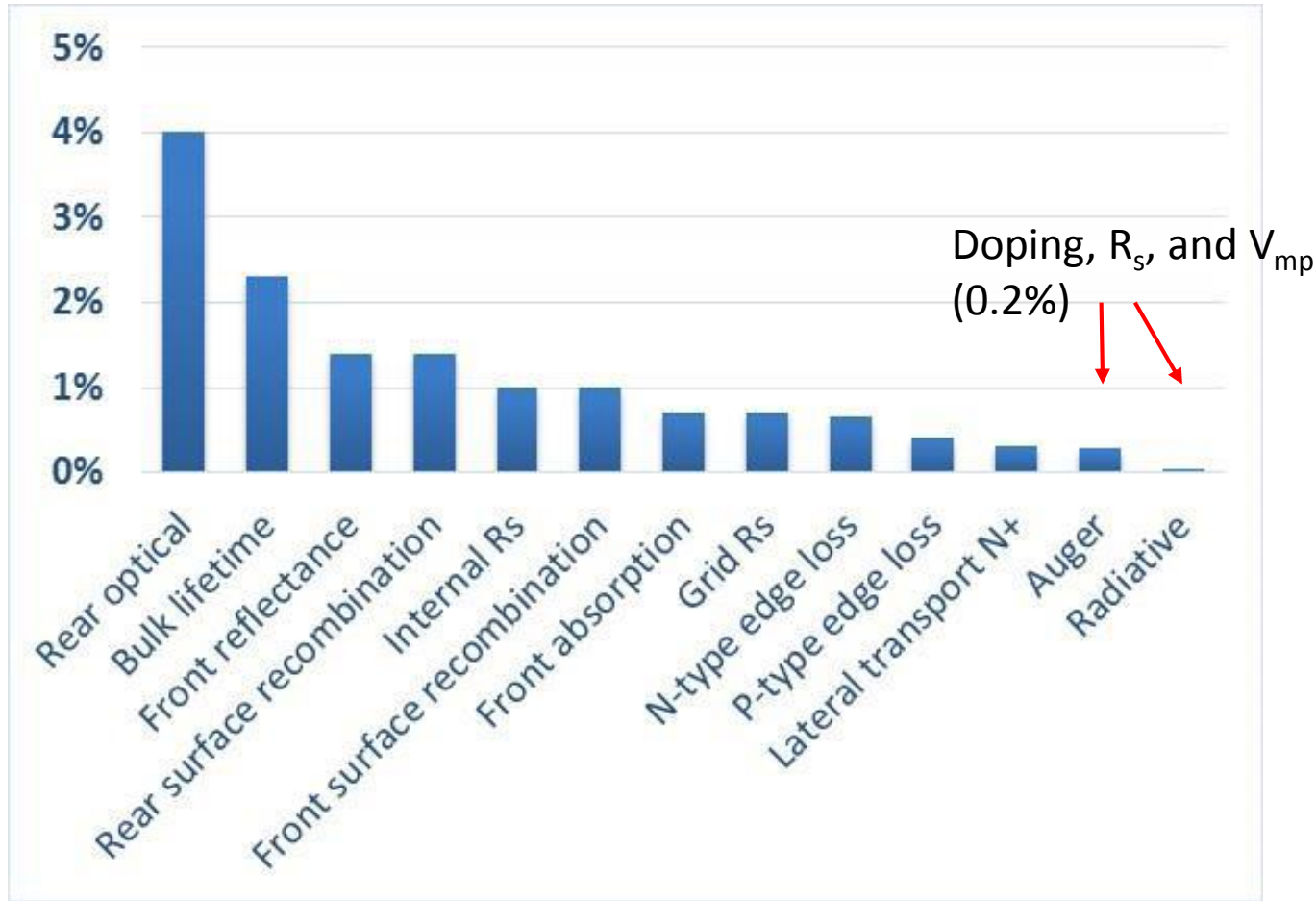
# Loss analysis: $J_0$ (front and back)



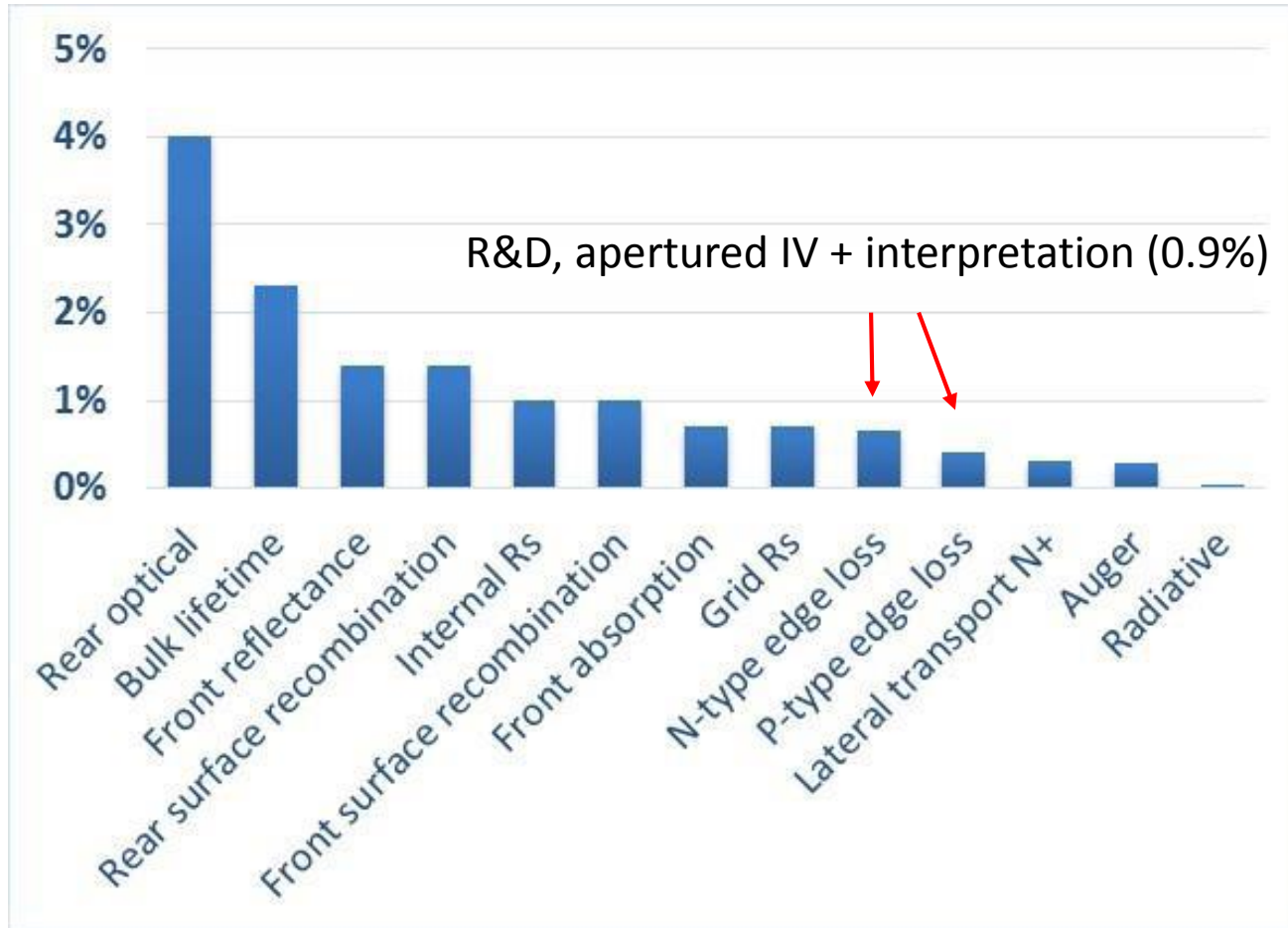
# Loss analysis: Sum of $R_s$ components



# Loss analysis: Fundamental recombination

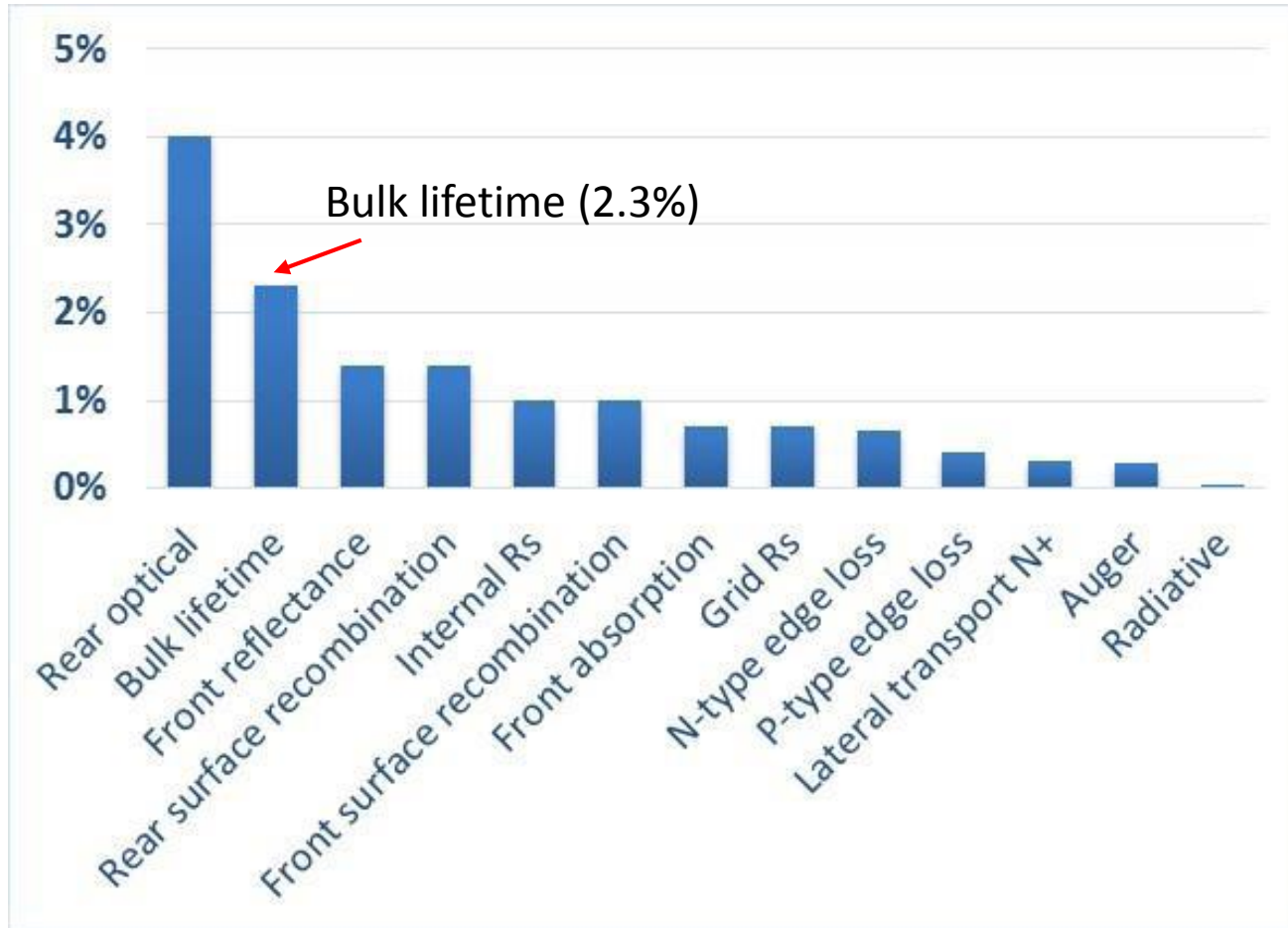


# Loss analysis: Inactive area/edge effects





# Loss analysis: Bulk Lifetime





# SunPower analysis from PVSC paper

## Test wafers prior to IV test (statistically significant)

TABLE II

INVERSE BULK LIFETIME FOR EMITTER TEST WAFERS.

Region	Front	Back 1	Back 2	Back 3	Area weighted average
Inverse bulk lifetime (1/sec)	17	16	64	44	50

=20 ms

But the bulk lifetime extracted at cell test was **6.7** ms, not 20 ms!

(use of lifetime vs. injection level data at cell test to determine bulk lifetime)

# SunPower analysis from PVSC paper

## Test wafers including “patterning”

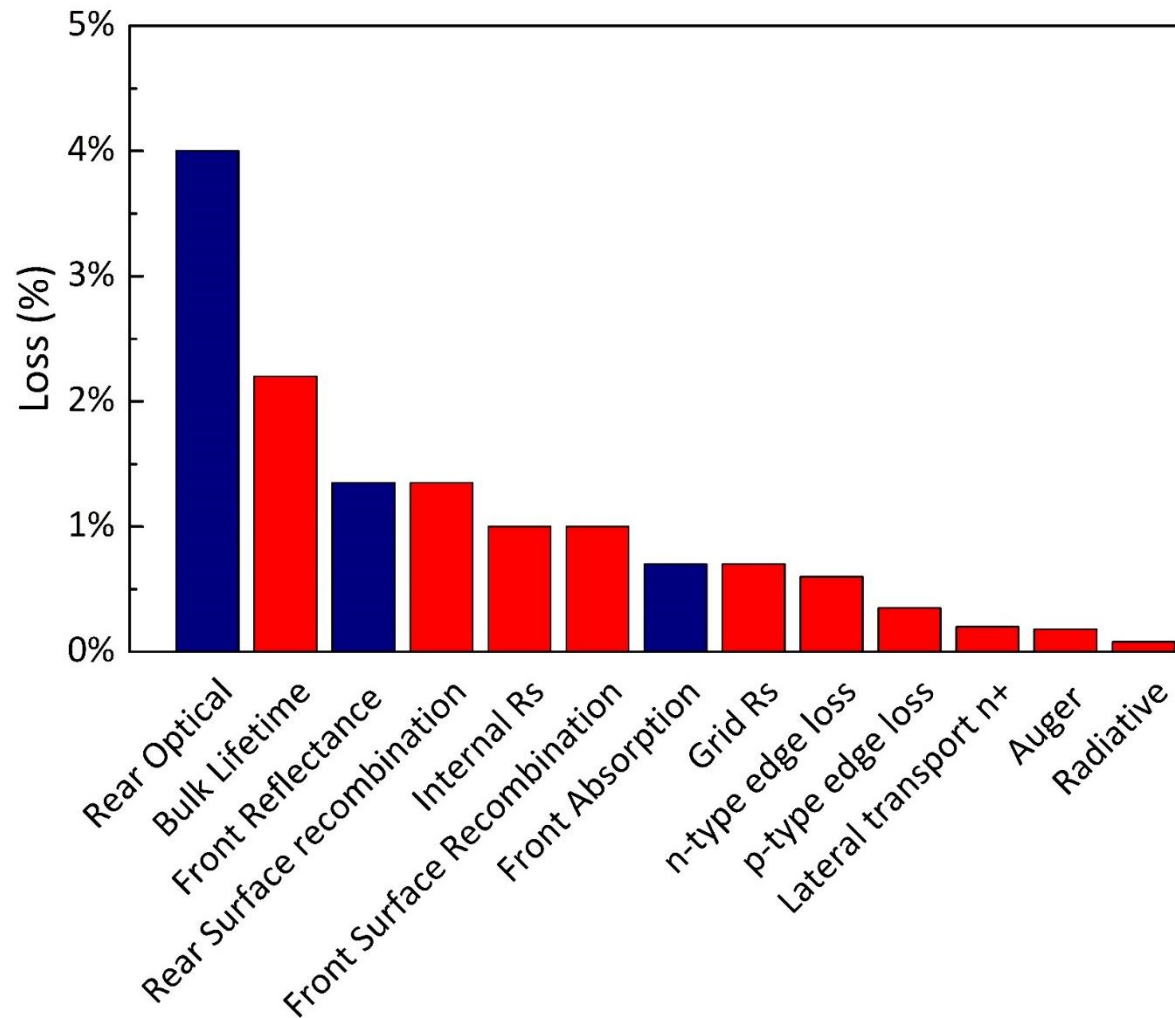
### INVERSE BULK LIFETIME FOR MAGNIFIED UNIT CELL TEST WAFERS

Region	Region 1	Region 2	Region 3	Area weighted average
Inverse bulk lifetime (1/sec)	66	161	173	143

=7 ms

Going back and including “patterning” steps in the lifetime tests for the regions of interest on test wafers matches the bulk lifetime of the cell at cell test.

# Loss analysis: Requires ext. spectral response + model



# Conclusions

- Advanced device physics can be performed at cell test
- Normal IV parameters + Suns- $V_{oc}$ ,  $\tau$  vs.  $\Delta n$ ,  $R_s$ ,  $R_{sh}$ , substrate doping
- Enables sophisticated loss analysis, wafer by wafer, at cell test
- Fully implemented in line-speed production tools
  - Max speed 4800/hr (measurement time = 200ms). Limited by wafer transport to 2400/hr at present
  - Big data enables resolution for discriminating efficiency dependence on process control, substrate doping, surface passivation
- Extends well-known device-physics tools to cells and modules
  - Reliability studies ( $\tau$  vs.  $\Delta n$ ) on cells as well as test wafers

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- The authors would like to acknowledge Trina Solar and the Photovoltaics Manufacturing Consortium (PVMC) from providing solar cells for this work
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